

In-Situ De-embedding (ISD)

Ching-Chao Huang
huang@ataitec.com

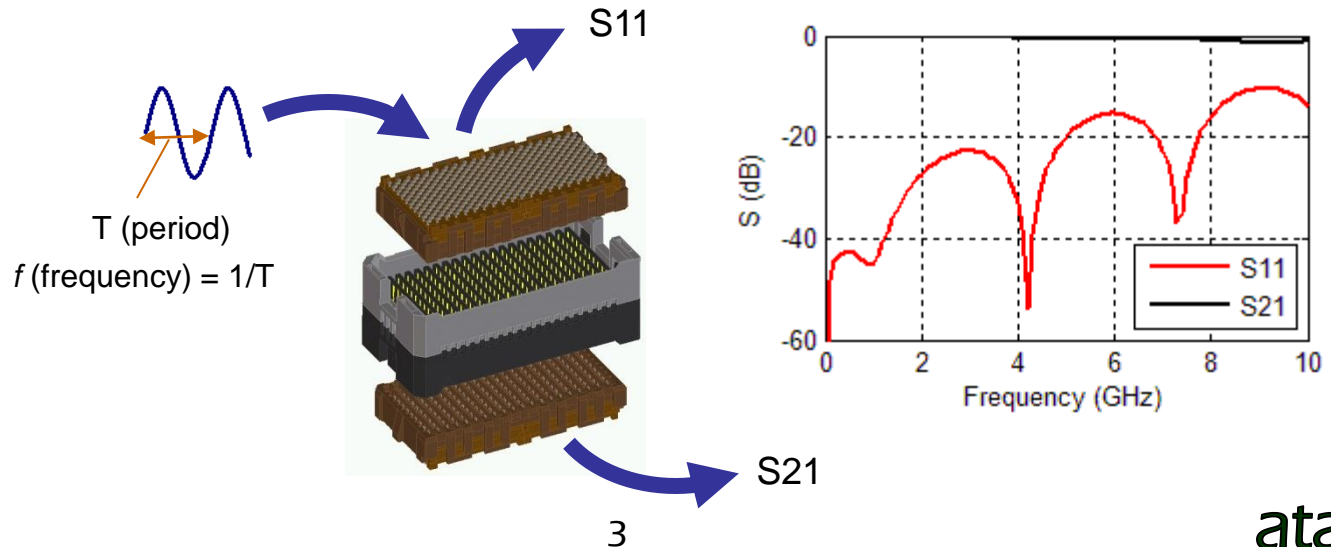
March 1, 2021

Outline

- 什么是因果关系
- 什么是原位去嵌入(ISD)
- ISD与仿真及其他软件比较
- 非因果去嵌入如何影响连接器一致性测试
- 如何提取没有尖峰和毛刺的准确的PCB走线衰减
- 如何通过匹配去嵌入的PCB走线的所有IL, RL, NEXT, FEXT和TDR / TDT特性来提取PCB的材料属性 (DK, DF, 粗糙度)

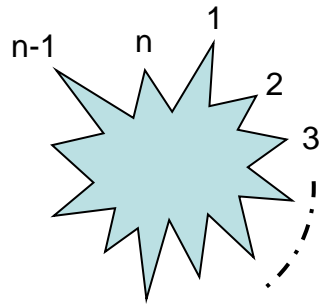
VNA and S parameter

- 网络分析仪（VNA）是一种将正弦波发射到某种结构中，改变波形的周期（或频率）使我们能够观察传输波和反射波的“频域响应”的设备
- 当将这种频域响应归一化为入射波时，称为散射参数（或S参数）



What is S parameter

- 对于n端口（或I / O）设备，S参数为n x n矩阵：



$$[S_{ij}]_{n \times n} = \begin{bmatrix} S_{11} & S_{12} & S_{13} & \dots & S_{1n} \\ S_{21} & S_{22} & S_{23} & \dots & S_{2n} \\ \vdots & \vdots & \vdots & \vdots & \vdots \\ S_{n1} & S_{n2} & S_{n3} & \dots & S_{nn} \end{bmatrix}$$

- S_{ij} 端口J到端口I的S参数
- S_{ij} 具有独特的性质，对于无源设备，其大小小于或等于1（或0 dB）

$$|S_{ij}| \leq 1$$

$$S_{ij} (dB) = 20 \times \log_{10} |S_{ij}| \leq 0 \text{ dB}$$

什么是Touchstone (.sNp) 文件

- 每个频率下的S参数以Touchstone文件格式表示

```
! Total number of ports = 4
! Total number of frequency points = 800
# GHZ S DB R 50
0.025 -36.59296 48.77486 -41.40676 79.91354 -0.08648679 -6.544144 -49.50045 -105.618
-41.39364 79.94686 -36.35592 51.52433 -49.4886 -105.5124 -0.09038406 -6.527076
-0.08421237 -6.537903 -49.44814 -105.644 -36.0317 49.60022 -41.37105 79.91856
-49.44393 -105.8186 -0.09834136 -6.542909 -41.36758 79.9318 -36.05645 48.98348
0.05 -32.22576 48.03161 -35.59394 74.15976 -0.1277169 -12.82876 -43.90183 -112.0995
-35.58736 74.16304 -32.12694 50.92389 -43.90926 -112.0764 -0.132402 -12.7985
-0.1242117 -12.82302 -43.89 -112.0248 -32.10987 50.3115 -35.56998 74.078
-43.88424 -112.0517 -0.1381616 -12.80199 -35.56758 74.06782 -31.94136 50.49276
0.075 -29.88861 42.02766 -32.19713 68.06704 -0.1589249 -19.05252 -40.67476 -118.8188
-32.19116 68.0941 -29.7086 45.41557 -40.63857 -118.837 -0.1635606 -19.01593
-0.1603356 -19.0376 -40.63557 -118.8543 -29.89064 47.63852 -32.16917 67.94677
-40.65711 -118.8021 -0.1737256 -19.02956 -32.16865 67.93389 -29.65444 46.15548
: : :
```

in GHz

S param

in dB and phase angle

Reference impedance

Frequency in GHz

S11, S12, ..., S44 in dB and phase angle

什么是因果关系

cau·sal·i·ty

/kô'zalədē/

noun

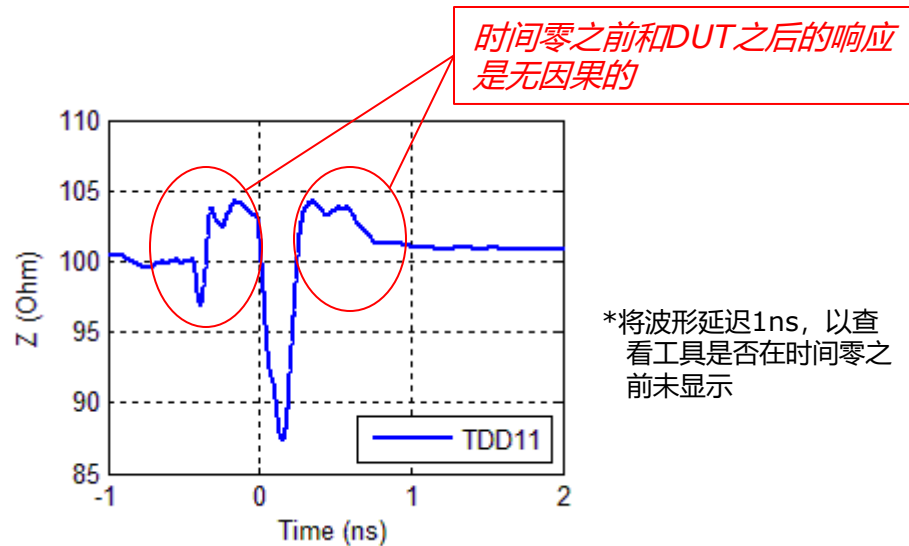
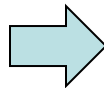
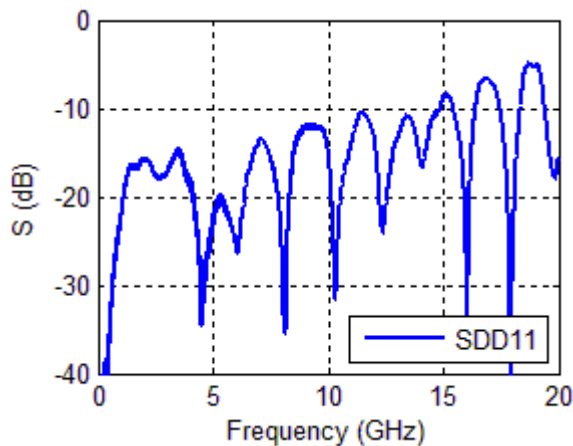
1. the relationship between cause and effect. 因果关系
2. the principle that everything has a cause.
一切都有原因的原则

In other words:

Can not get something from nothing.

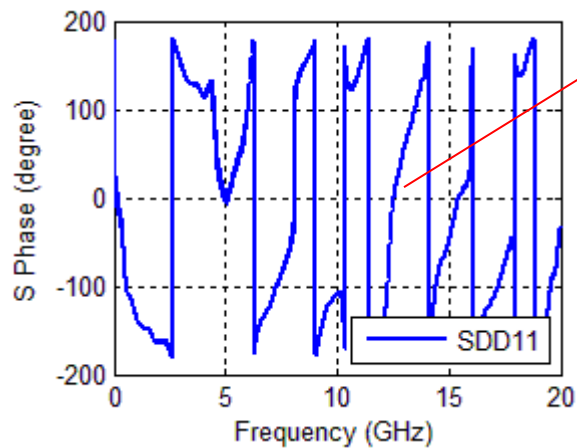
如何识别非因果S参数

- 把S参数转换成TDR/TDT.



*将波形延迟1ns, 以查看工具是否在时间零之前未显示

- 相位.



逆时钟相位角是无因果的

为什么S参数违反因果关系

- 测量误差（去嵌入），模拟误差（材料特性）和S参数的有限带宽都造成了非因果关系。
- Kramers-Kronig关系要求解析函数的实部和虚部通过希尔伯特变换相互关联：

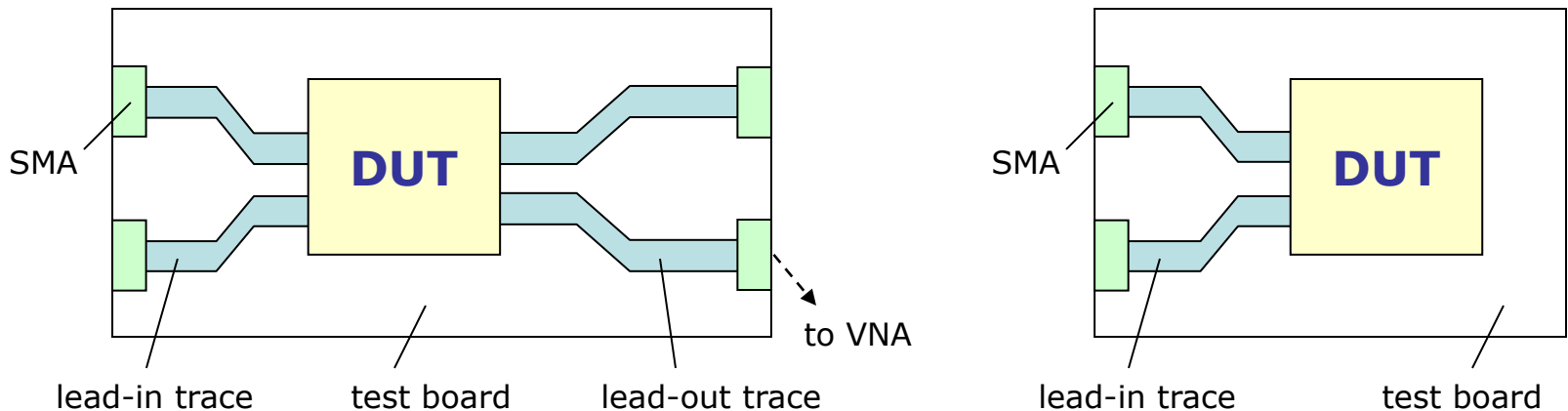
$$\Psi(\omega) = \Psi_R(\omega) + j\Psi_I(\omega)$$

$$\Psi_R(\omega) = \frac{1}{\pi} P \int_{-\infty}^{\infty} \frac{\Psi_I(\omega')}{\omega' - \omega} d\omega'$$

$$\Psi_I(\omega) = -\frac{1}{\pi} P \int_{-\infty}^{\infty} \frac{\Psi_R(\omega')}{\omega' - \omega} d\omega'$$

什么是去嵌入

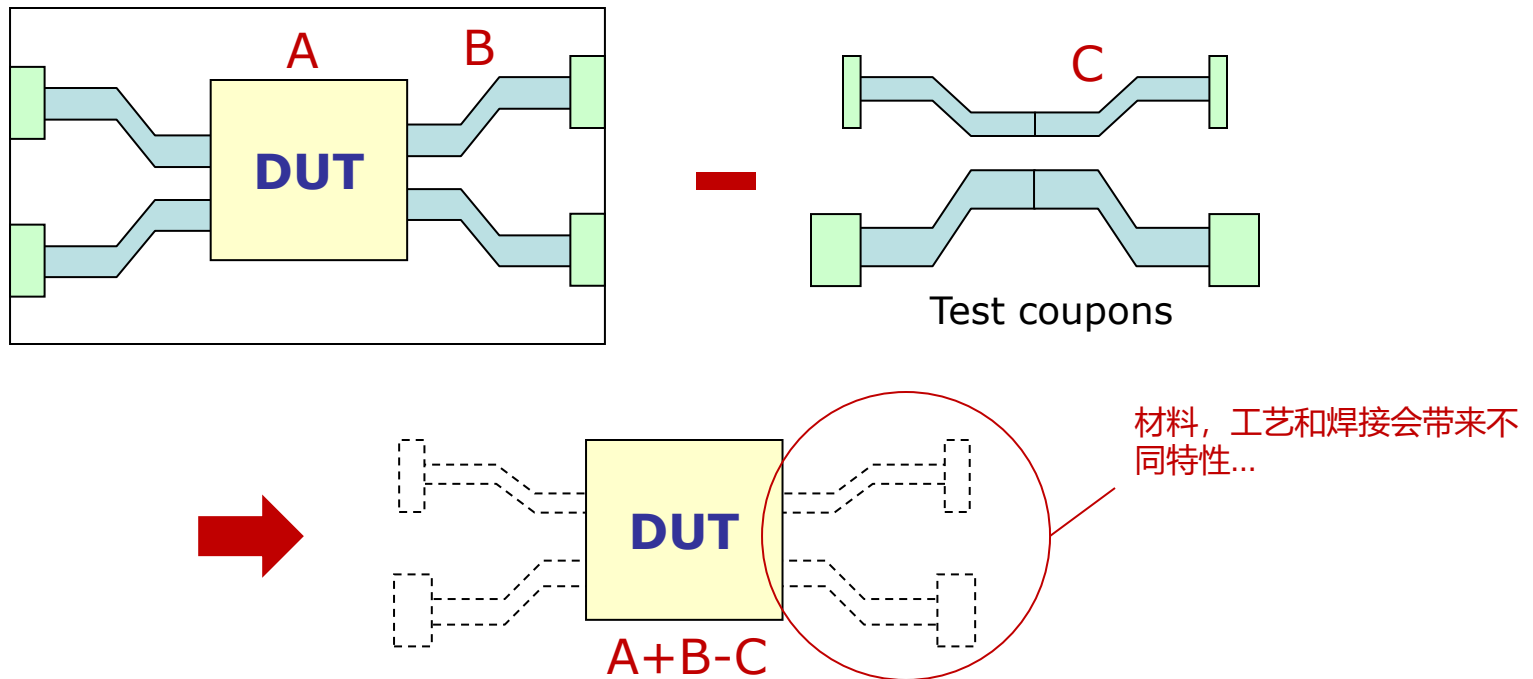
- 消除夹具（SMA连接器+导入/导出）的影响并提取DUT（被测设备）的S参数



- 引入和引出走线不一定要相同
- 有许多器件甚至没有引入和引出走线(如芯片封装).

为什么大多数去嵌入工具都会导致因果关系错误

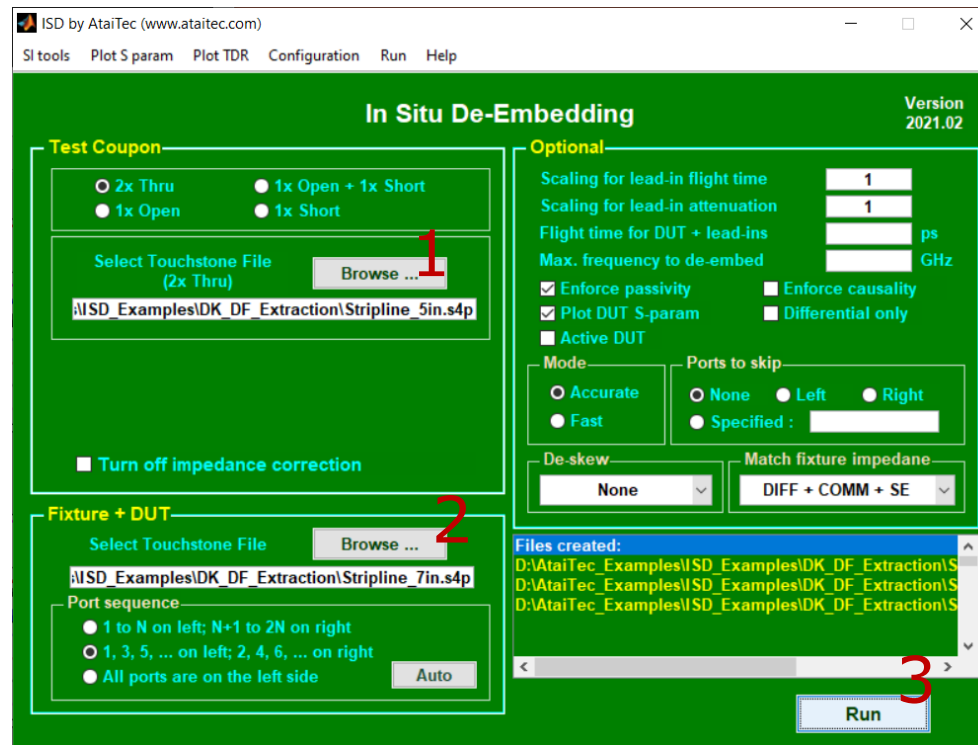
- 大多数工具直接使用测试样板进行去嵌入，因此实际夹具和测试样板之间的差异会累积到DUT结果中。



* <http://www.edn.com/electronics-blogs/test-voices/4438677/Software-tool-fixes-some-causality-violations> by Eric Bogatin

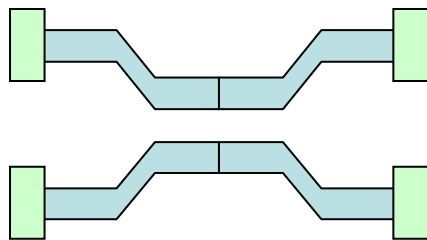
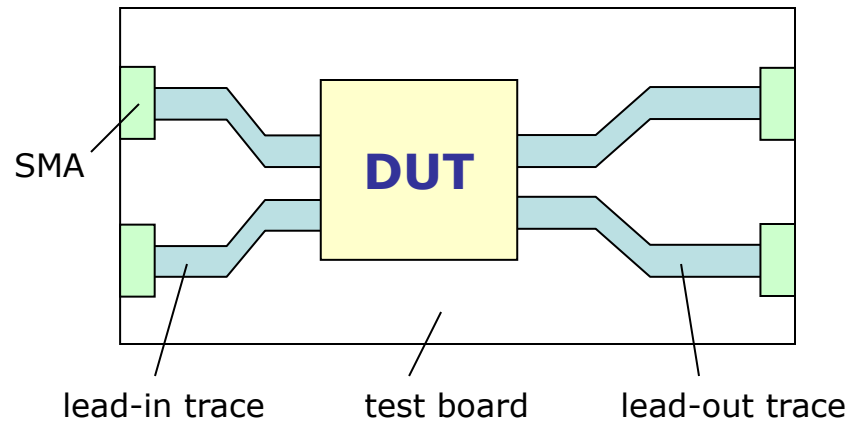
介绍什么是原位去嵌入 (ISD) 以解决阻抗变化

- ISD使用测试校准件 (“2x thru”或“1x open / 1x short”) 作为参考，并通过数值优化对夹具的实际阻抗进行去嵌入
- 其他方法直接使用测试校准件进行去嵌入，而当测试校准件和要去嵌入的实际夹具具有不同的阻抗时，会导致因果关系错误
- ISD通过软件而非硬件解决了测试校准件和实际夹具之间的阻抗变化，从而提高了去嵌入精度并降低了硬件成本。

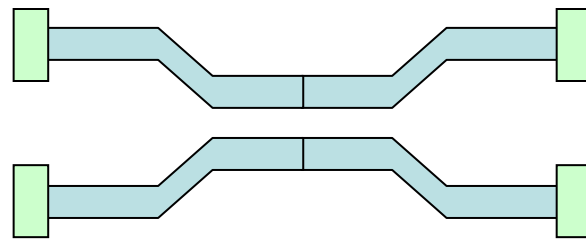


什么是“2x thru”

- “2x thru” 是 2x lead-ins引入走线 或lead-outs引出走线.



2x thru for lead-ins

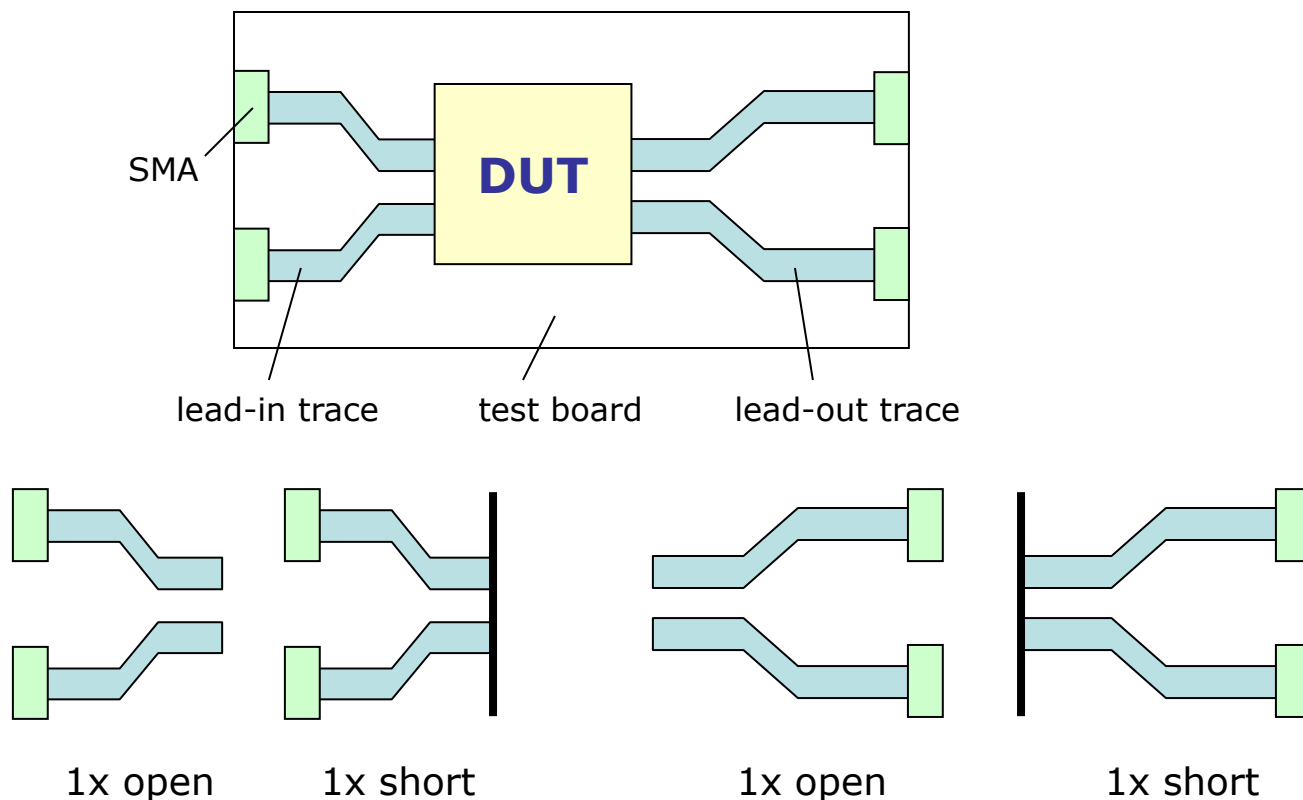


2x thru for lead-outs

非对称夹具需要2套“2x thru”

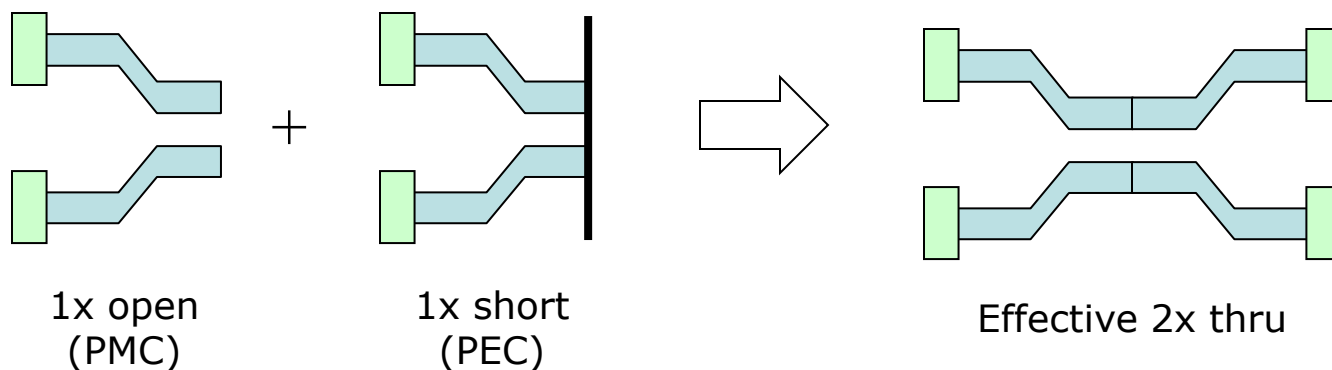
什么是“1x open / 1x short”

- “1x open / 1x short” 是当“2x thru”不可用时(如连接器, 过孔, 封装等)采用.



什么是“1x open + 1x short”

- “1x open + 1x short” 可以等效为2x thru.

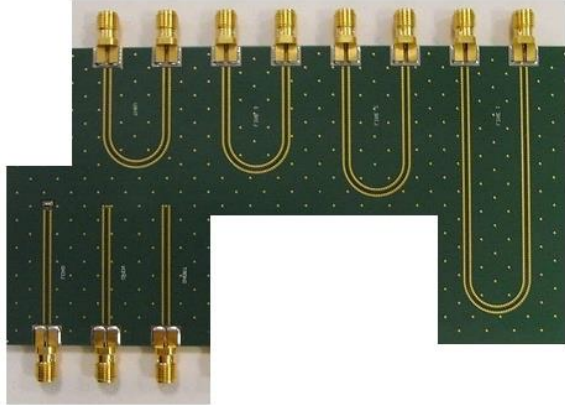


$$[S]^{2x} = \begin{bmatrix} S_{11}^{2x} & S_{12}^{2x} \\ S_{12}^{2x} & S_{11}^{2x} \end{bmatrix} = \frac{1}{2} \begin{bmatrix} S_{11}^{\text{open}} + S_{11}^{\text{short}} & S_{11}^{\text{open}} - S_{11}^{\text{short}} \\ S_{11}^{\text{open}} - S_{11}^{\text{short}} & S_{11}^{\text{open}} + S_{11}^{\text{short}} \end{bmatrix}$$

* C.C. Huang, "Fixture de-embedding using calibration structures with open and short terminations," US patent no. 9,797,977, 10/24/2017.可以参考这个专利

为什么ISD是更精准又经济?

TRL calibration board



- 更大的电路板空间-需要多个测试校准线路.
- 测试校准件直接用于去嵌入
- 校准件和实际DUT板之间的所有差异都会累积到DUT结果中
- 需要优质但昂贵的SMA, PCB材料 (Roger) 和严格的公差工艺要求-不可能保证所有的连接器和PCB工艺都绝对相同
- 需要耗时的手动校准-参考平面在DUT的前面

ISD test coupon

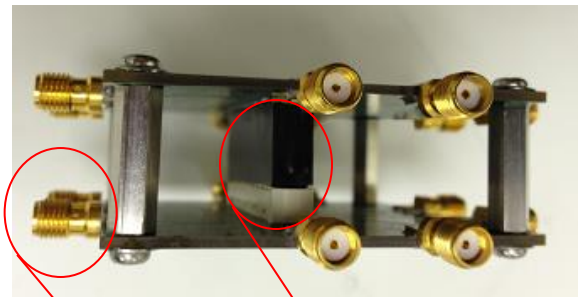


- 只需一张2xthru 测试校准件.
- 测试校准件仅用于参考, 不用于直接去嵌入
- 实际的DUT板阻抗被去嵌入
- 可以采用一般的连接器和PCB材料以及PCB制程工艺
- 电子校准可以用于SOLT 校准.
 - 参考平面在SMA前面
 - 去嵌入仅需要两个输入文件: 2xthru和DUT板 (SMA至SMA) 的Touchstone文件.
 - 更多信息: 可以输出去嵌入和DUT文件

* TRL = Thru-Reflect-Line

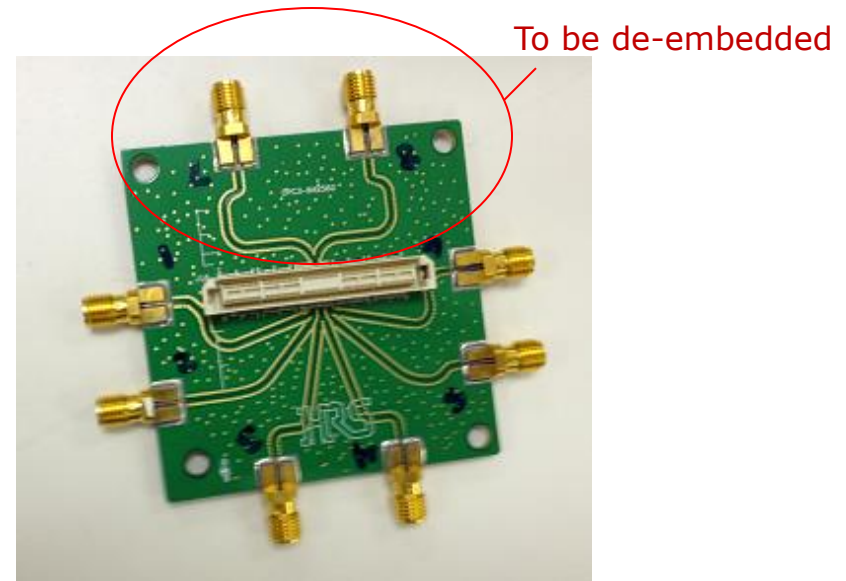
示例1：夹层连接器的测试 ISD与TRL比较

- 在此示例中，我们将使用ISD和TRL提取夹层连接器的性能并比较它们的结果



SMA

Mezzanine
connector
(DUT)

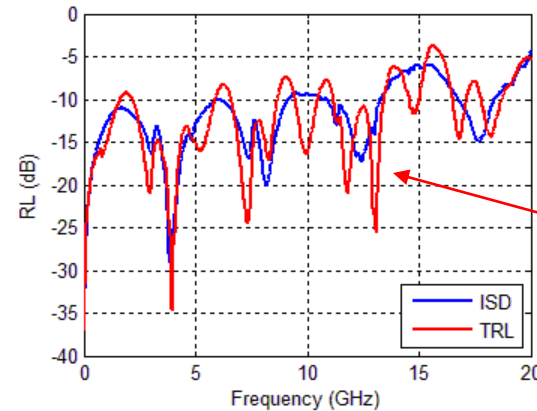
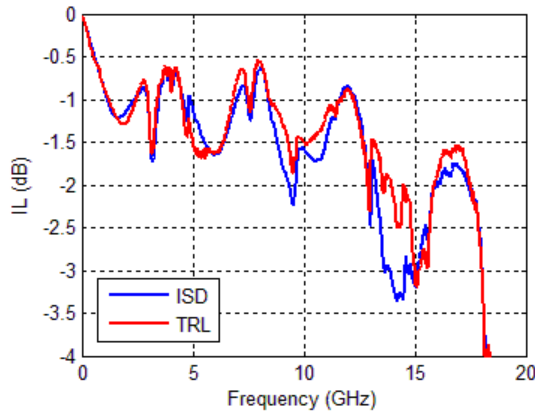


To be de-embedded

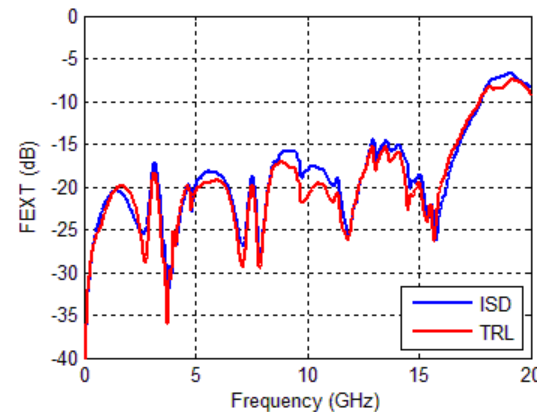
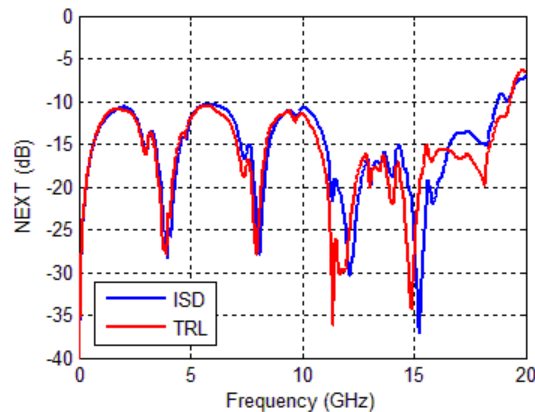
*Courtesy of Hirose Electric

使用ISD和TRL之后的DUT结果哪个更准确？

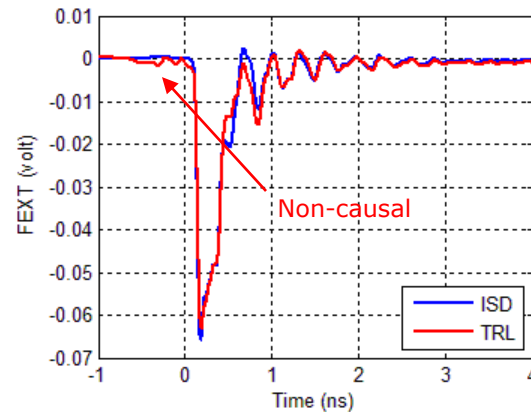
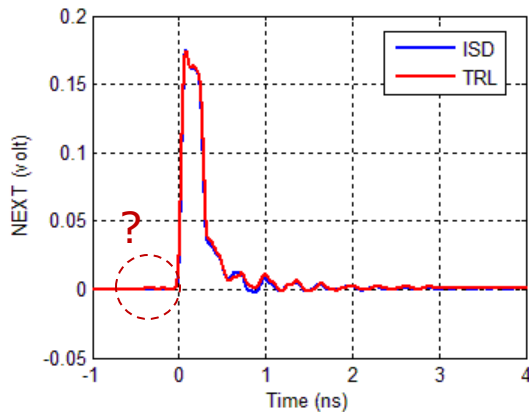
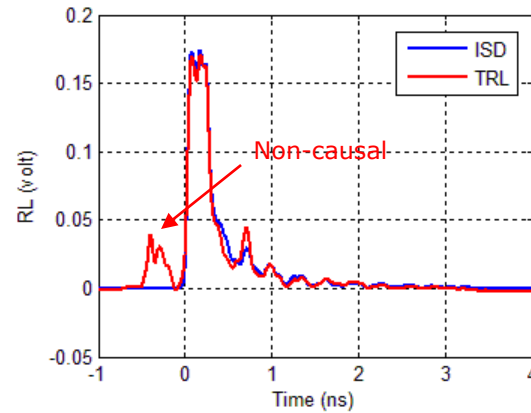
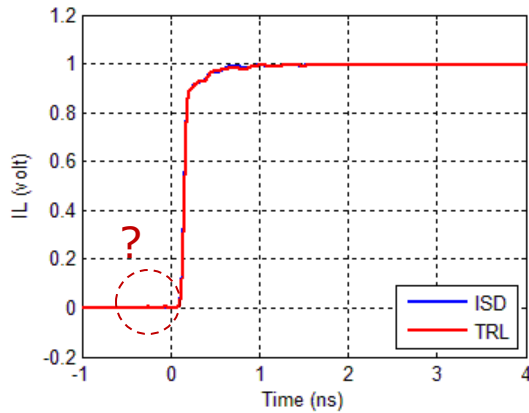
- 对于这么小的DUT，TRL会在回波损耗（RL）中产生过多的纹波



Non-causal ripples



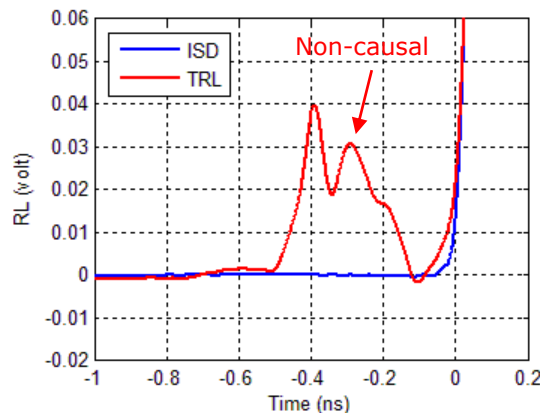
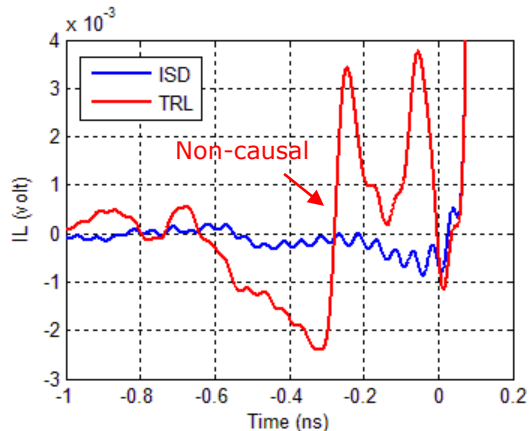
将S参数转换为TDR / TDT显示TRL的方法中有非因果关系的反射



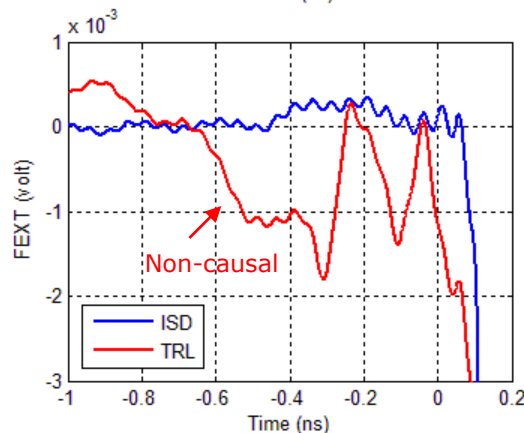
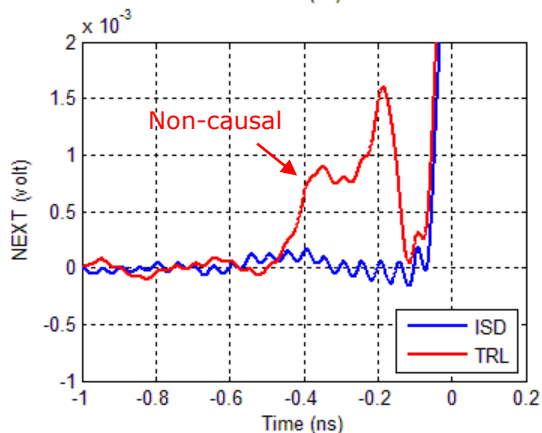
Rise time = 40ps (20/80)

放大显示所有TRL方法中IL, RL, NEXT和FEXT的非因果结果

- 在这种情况下，TRL导致时域误差为0.38% (IL) , 25.81% (RL) , 1.05% (NEXT) 和2.86% (FEXT)
*



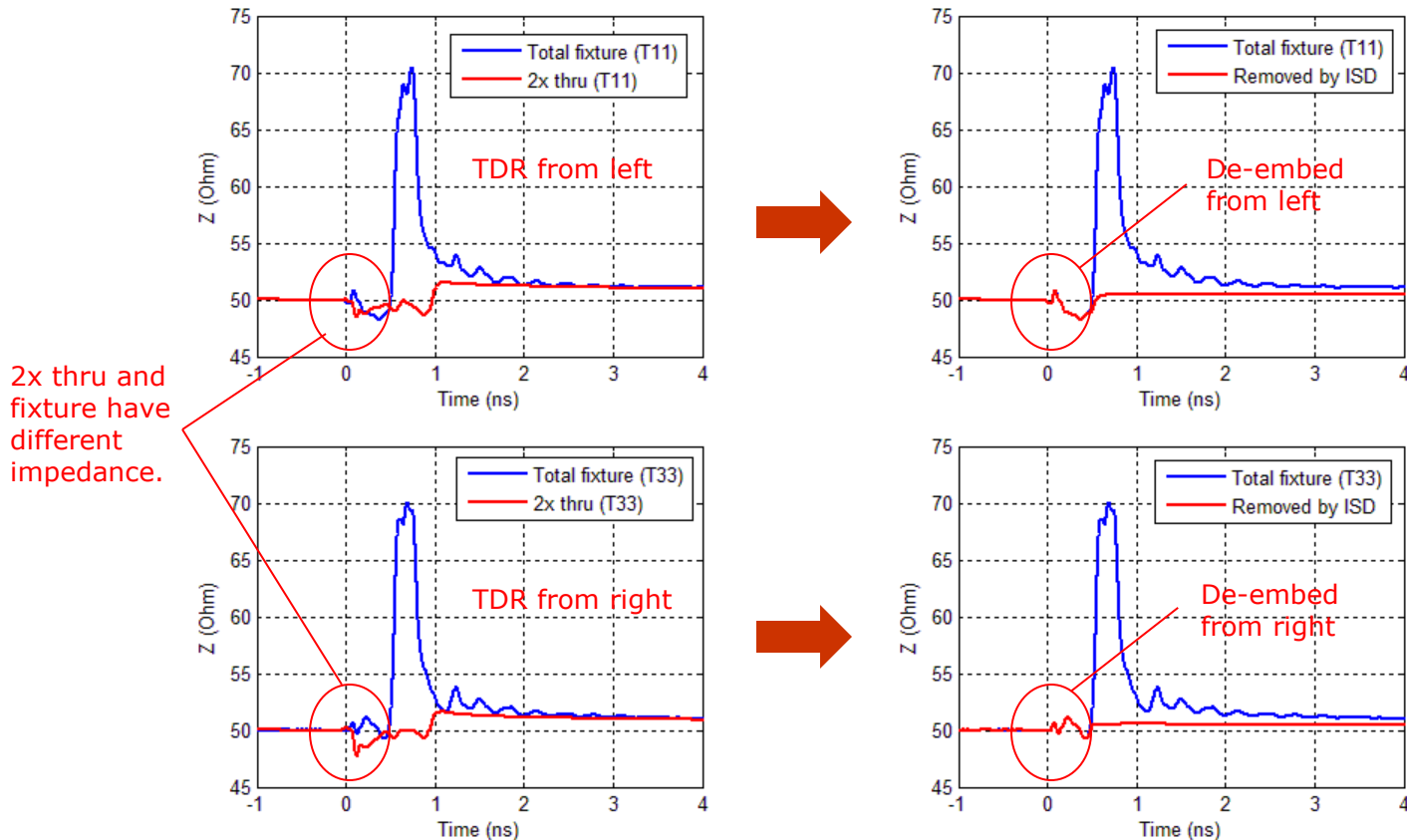
*使用一位响应和/或更快的上升时间时，该百分比会更大



Rise time = 40ps (20/80)

ISD是怎么做的？

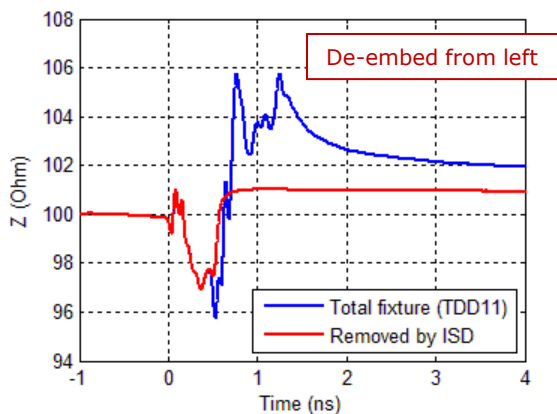
- 通过数值优化，ISD可以准确地去嵌入夹具的阻抗，而不受2xThru校准件的阻抗的影响。



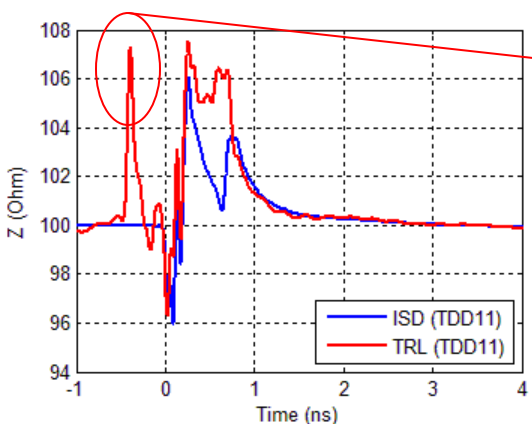
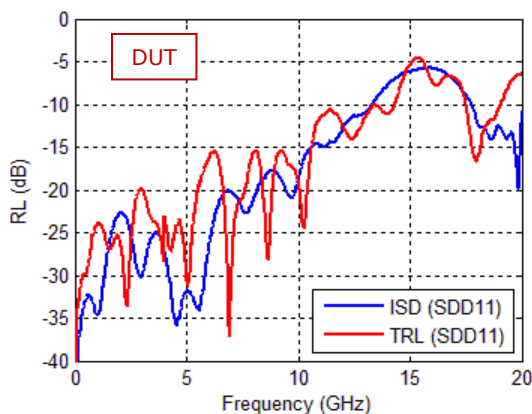
Rise time = 40ps (20/80)

即使阻抗变化很小，TRL也会在SDD11中产生巨大的误差*

- ISD只需单根走线的2xthru校准件即可去嵌入夹具的差分阻抗。



* 2xthru与夹具之间的阻抗变化小于5%。（请参阅上一张幻灯片）。

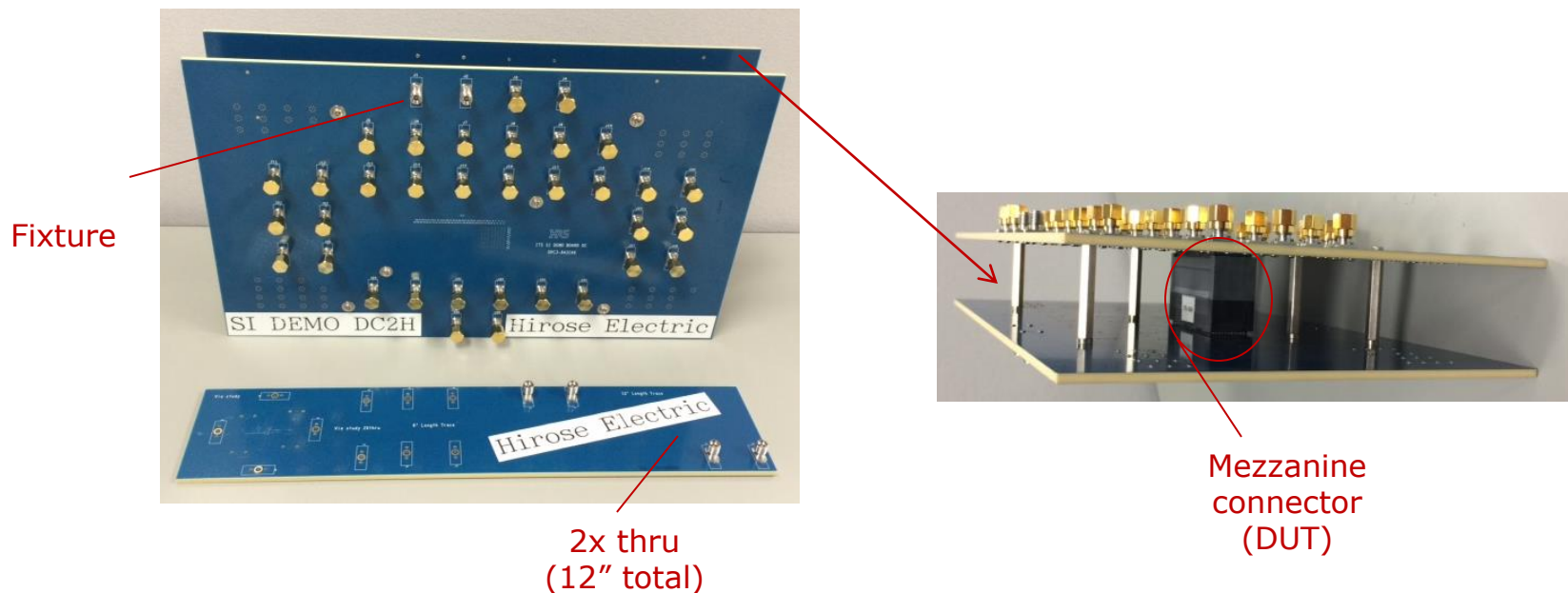


由于违反因果关系，TRL给出了超过100%的错误。

Rise time = 40ps (20/80)

示例2：夹层连接器性能从大板上提取

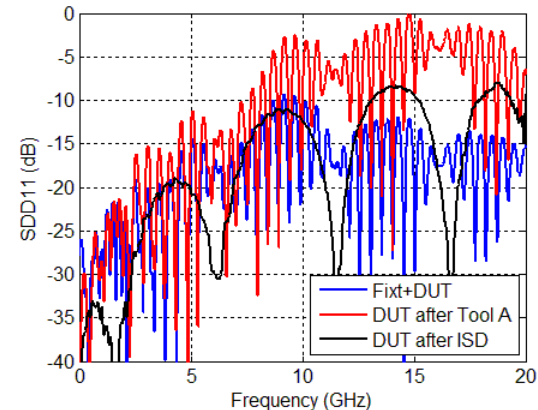
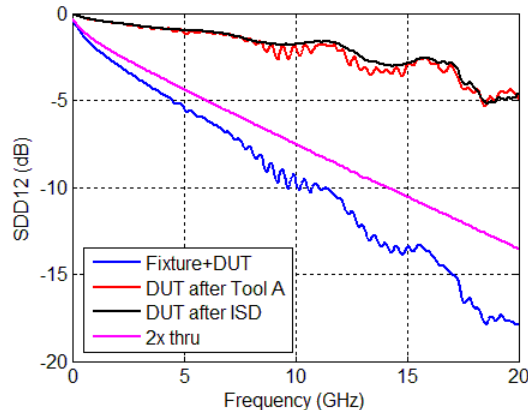
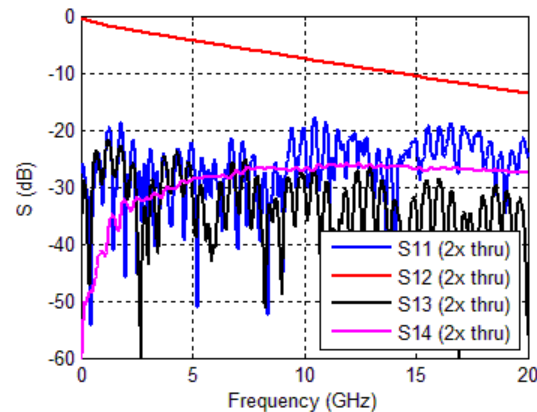
- TRL对于去嵌入大的和有耦合的引入/引出是不实用的。



ISD可以使用2xthru的.s4p文件进行去嵌入

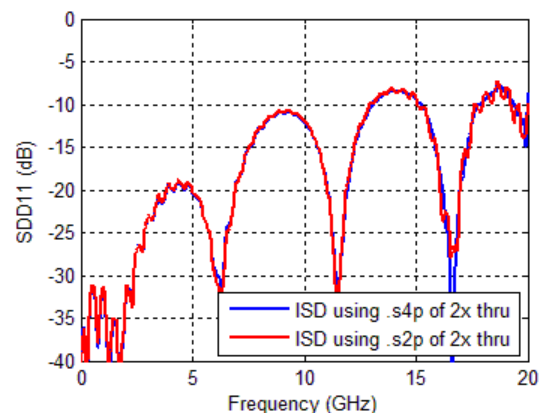
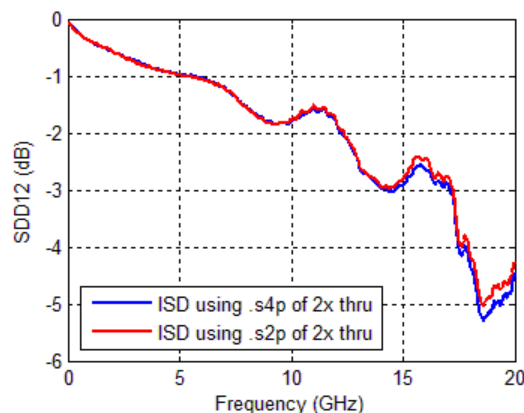
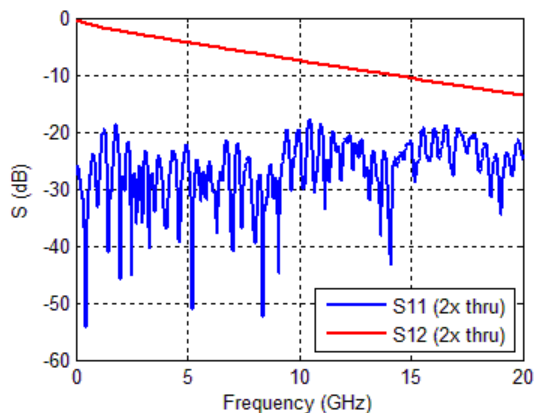
- TRL需要许多长且耦合的走线。

工具A给出了错误的结果



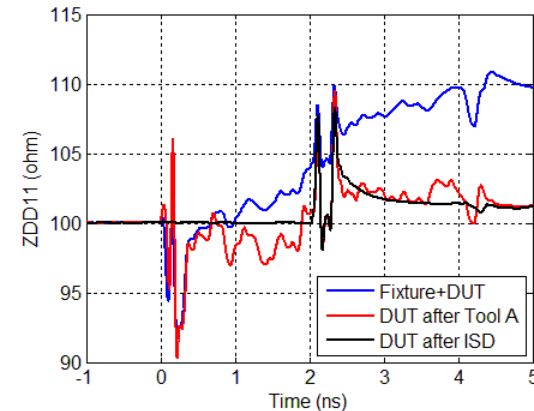
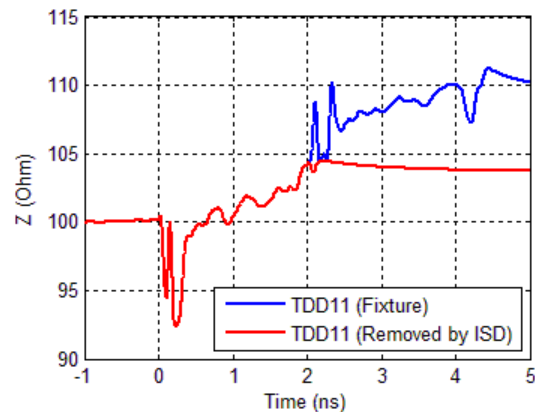
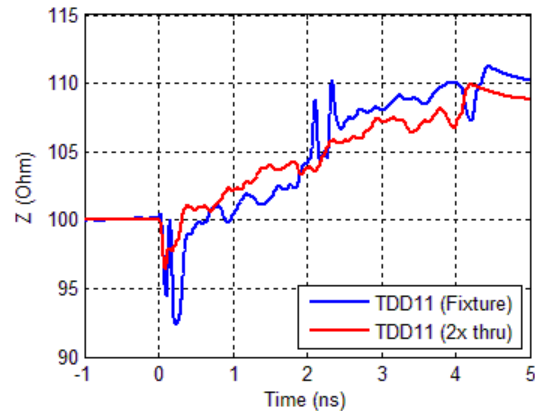
ISD甚至可以使用2xthru的.s2p文件来去嵌入串扰

- And the results are similar!



ISD允许大型演示板兼作特征板

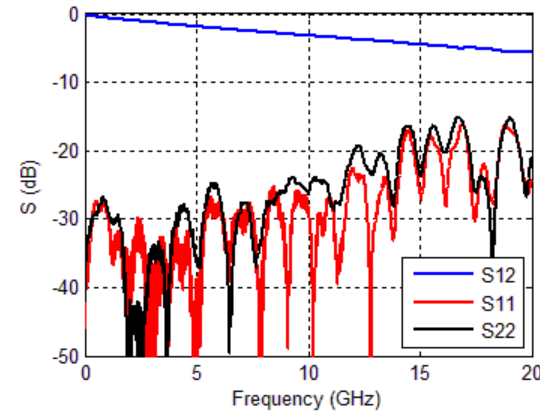
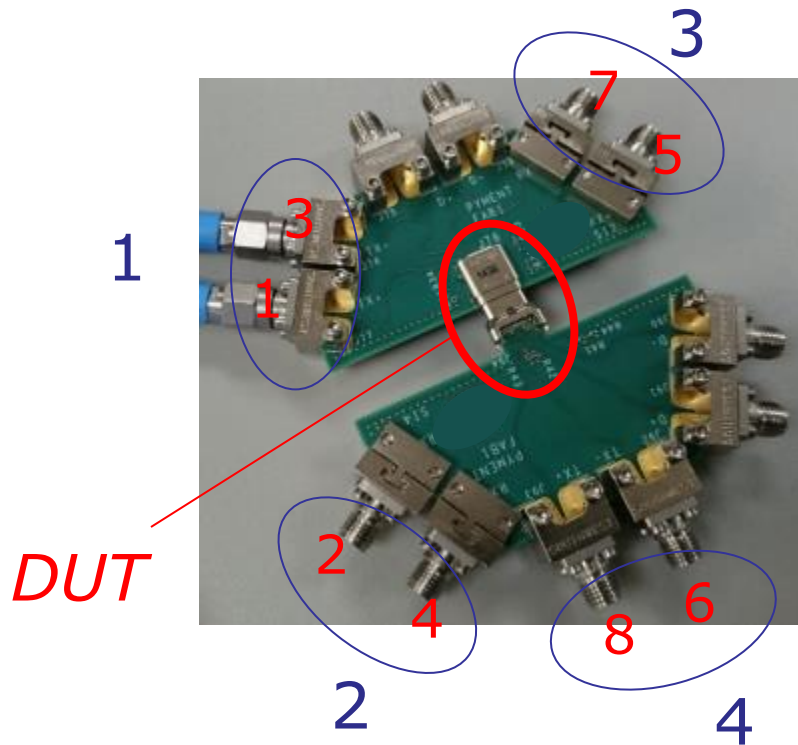
- ISD会去嵌入夹具的阻抗，而不管2xthru的阻抗。



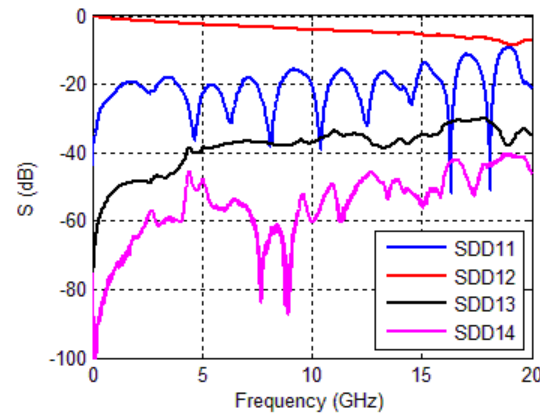
Rise time = 40ps (20/80)

示例3：USB C型连接器性能测试 ISD与工具A

- 良好的去嵌入对于满足合规性规范至关重要



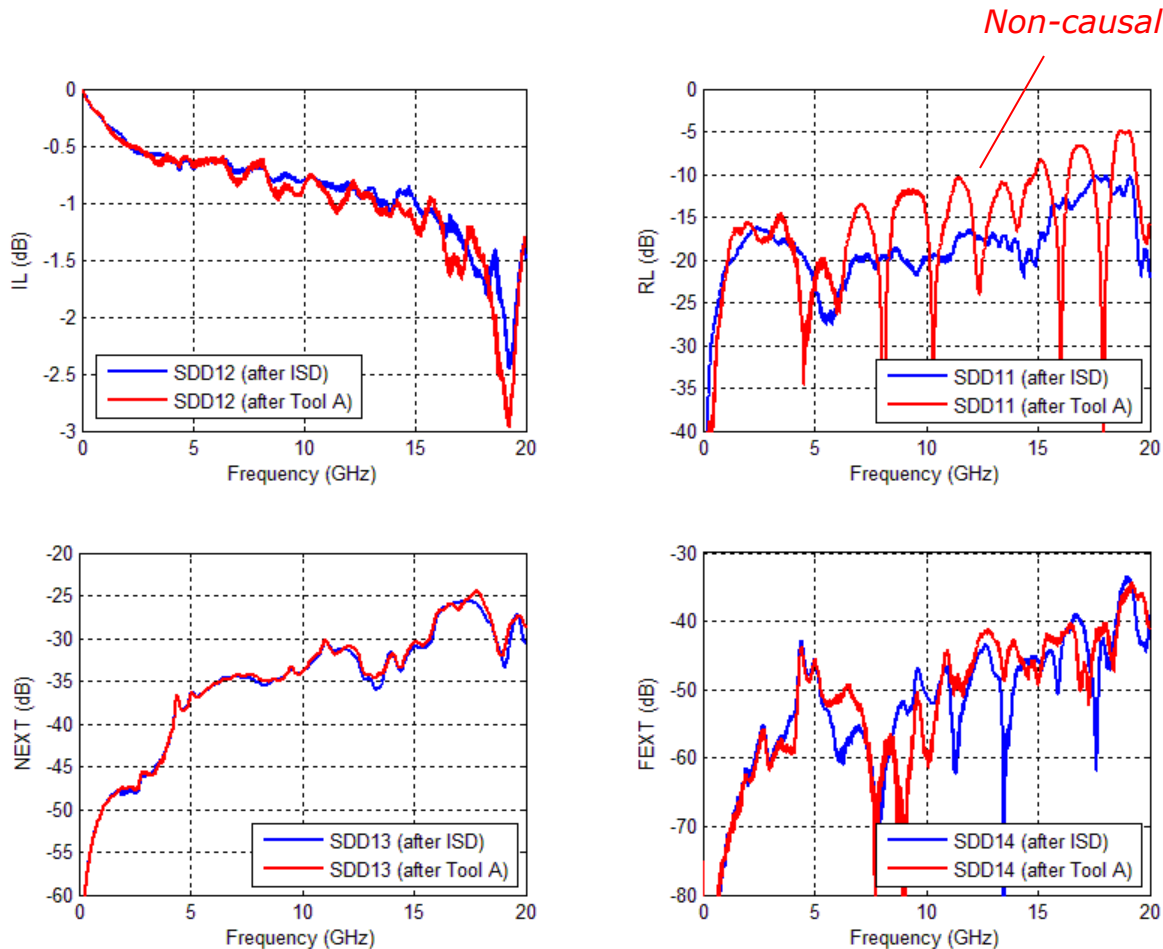
2x thru



Fixture

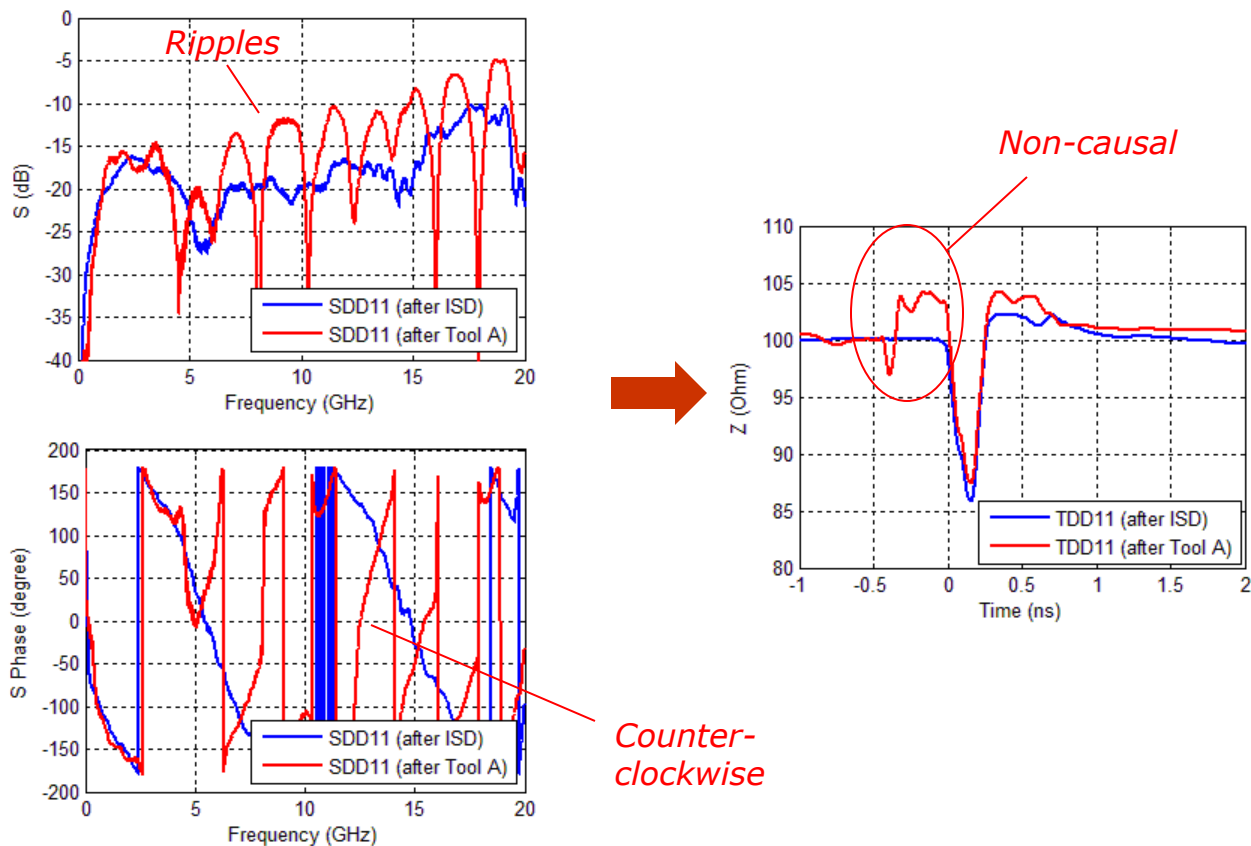
使用ISD和工具A之后的DUT结果哪个更准确？

- Tool A 的结果对于这么小的DUT来说在回损 (RL) 上有太多纹波



将S参数转换为TDR / TDT显示工具A的结果非因果性

- 逆时钟相位角是无因果关系的另一个指标。

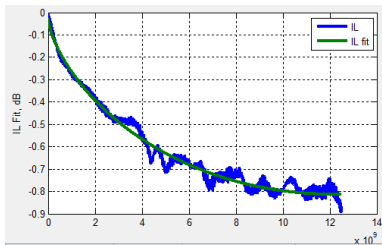


去嵌入会影响合规性规范测试的通过或失败

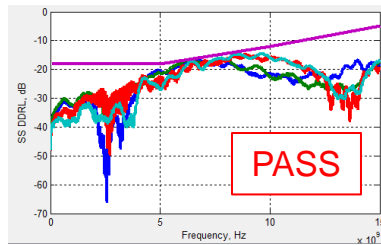
- ISD改进了IMR和IRL (通过合规性工具)

ISD

	Value (Pass/Fail)
ILfit@2.5GHz	-0.4
ILfit@5.0 GHz	-0.6
ILfit@10.0GHz	-0.8
IMR	-45.1
IRL	-23.2
INEXT	-41.5
IFEXT	-49.2
SCD12/SCD21	-23



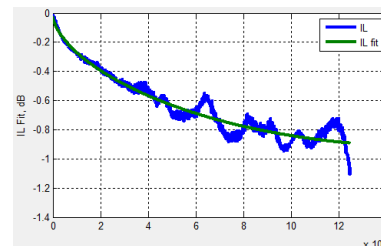
IL



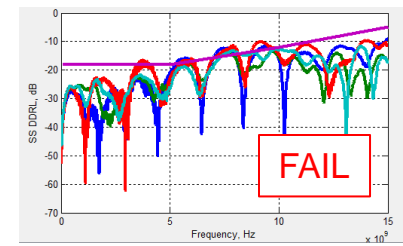
RL

Tool A

	Value (Pass/Fail)	Spec
ILfit@2.5GHz	-0.4	-0.6
ILfit@5.0 GHz	-0.6	-0.8
ILfit@10.0GHz	-0.9	-1.0
IMR	-43.7	-40
IRL	-20.8	-18
INEXT	-41.5	-44
IFEXT	-49.3	-44
SCD12/SCD21	-23.2	



IL

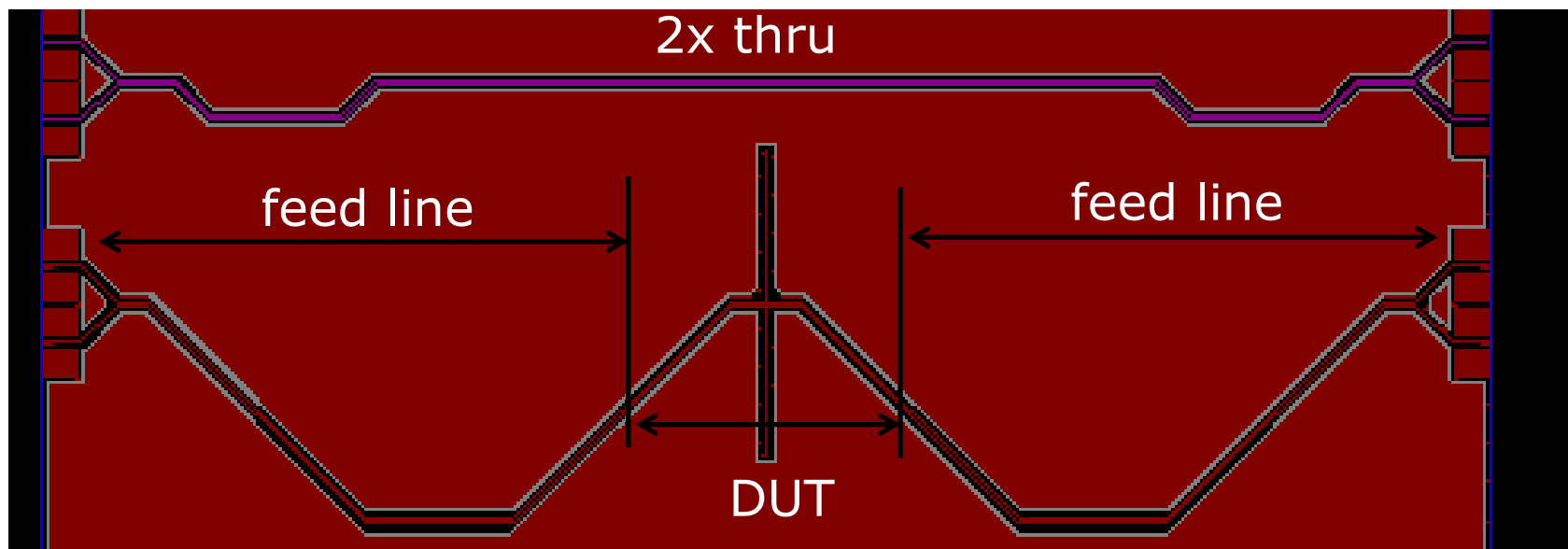


RL

示例4：谐振器

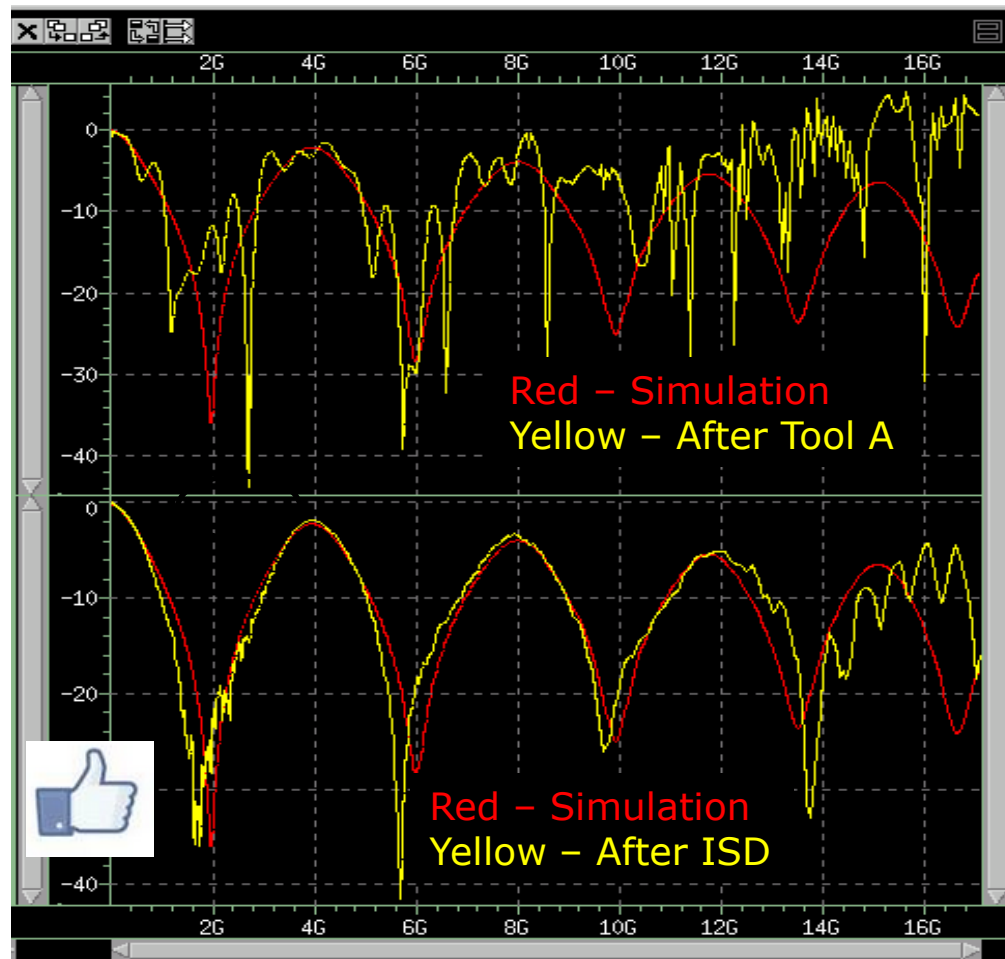
ISD，工具A，仿真之间的比较

- 良好的去嵌入对于设计验证（即相关性）和改进至关重要。



SDD11

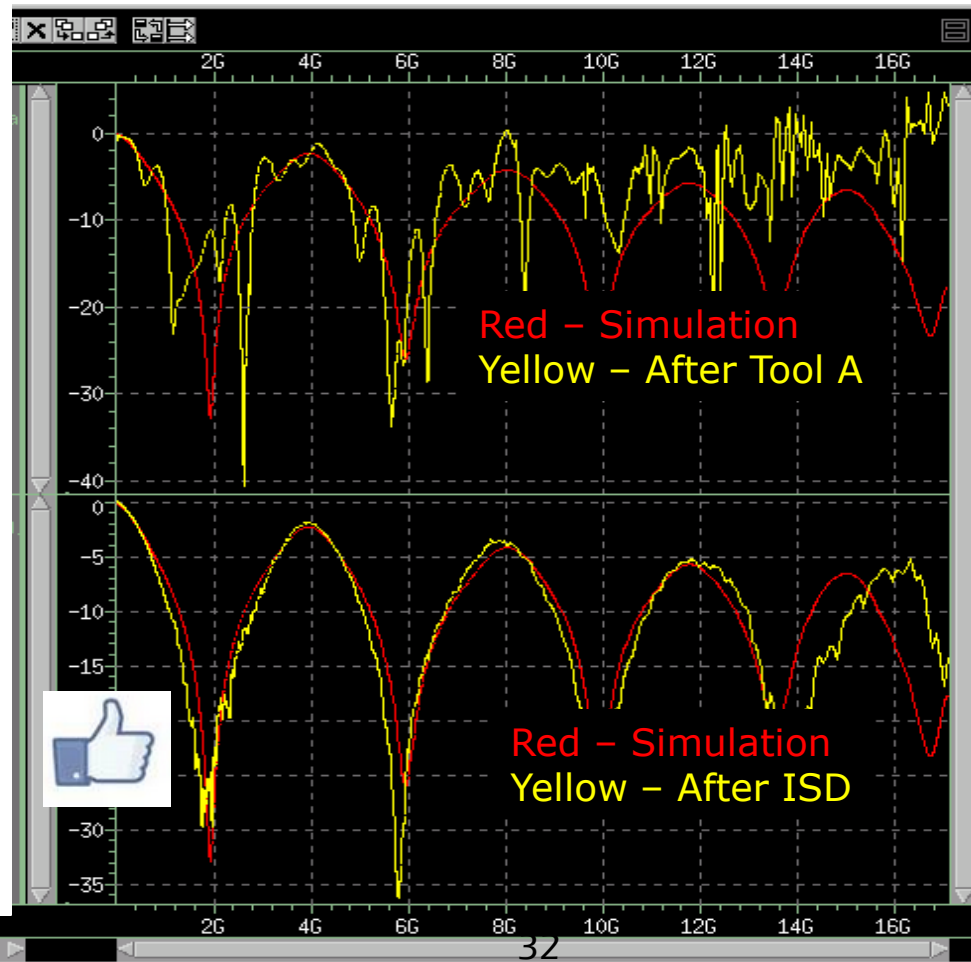
ISD与仿真的相关性



SCC11

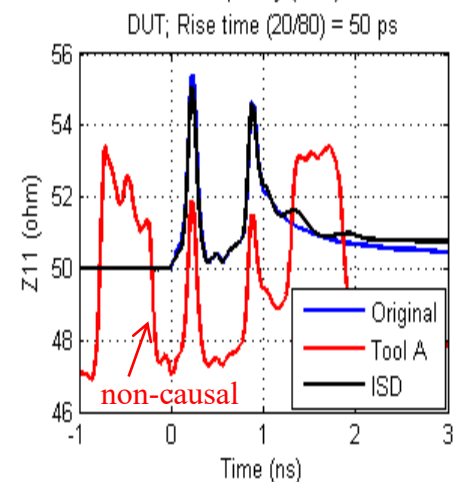
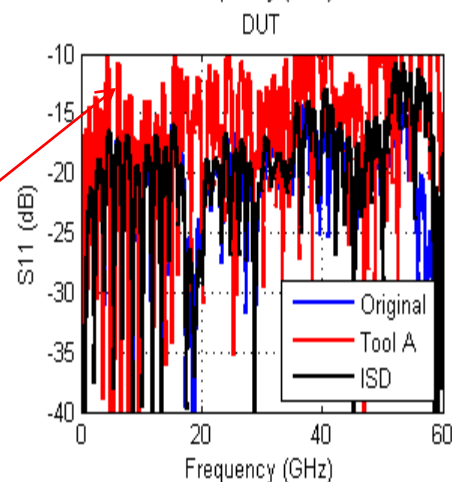
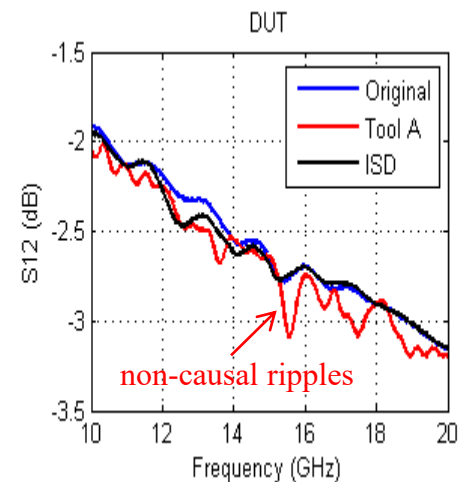
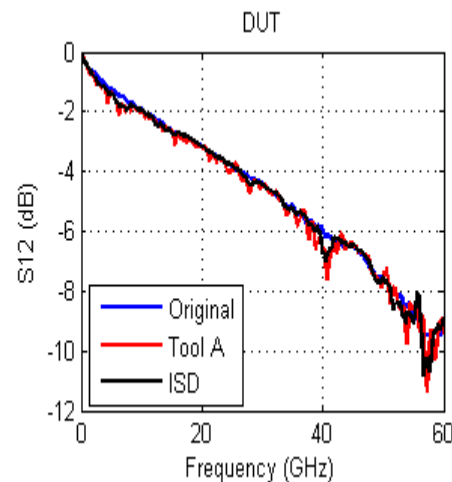
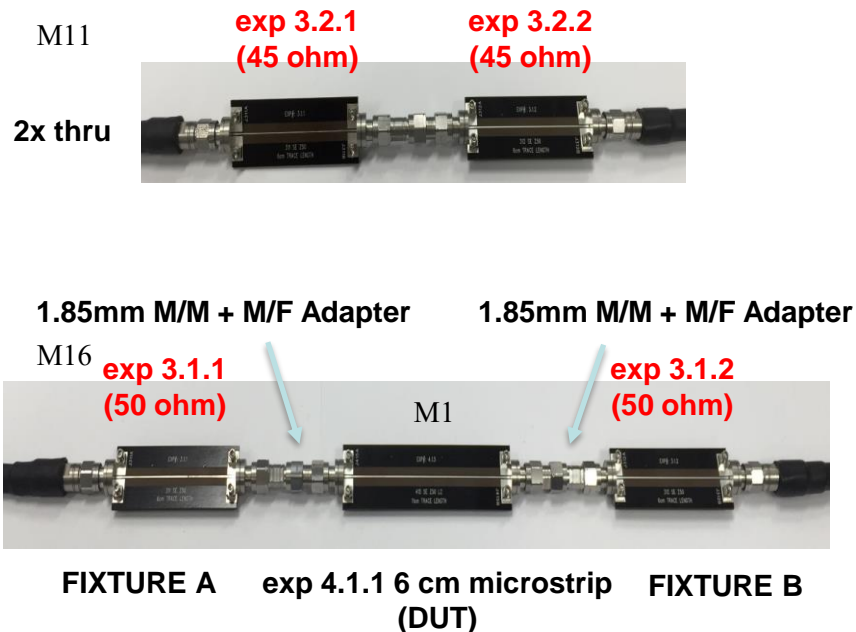
ISD与仿真的相关性

- 良好的相关性对于改进设计至关重要。



示例5: IEEE P370即插即用套件使用45欧姆 2XThru去嵌入50欧姆夹具*

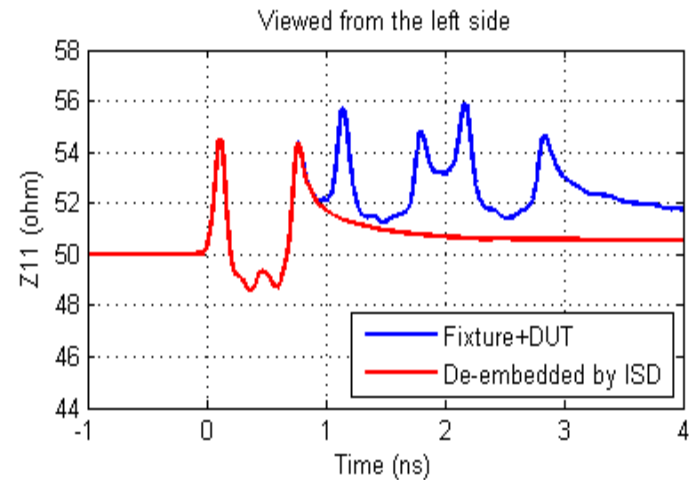
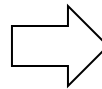
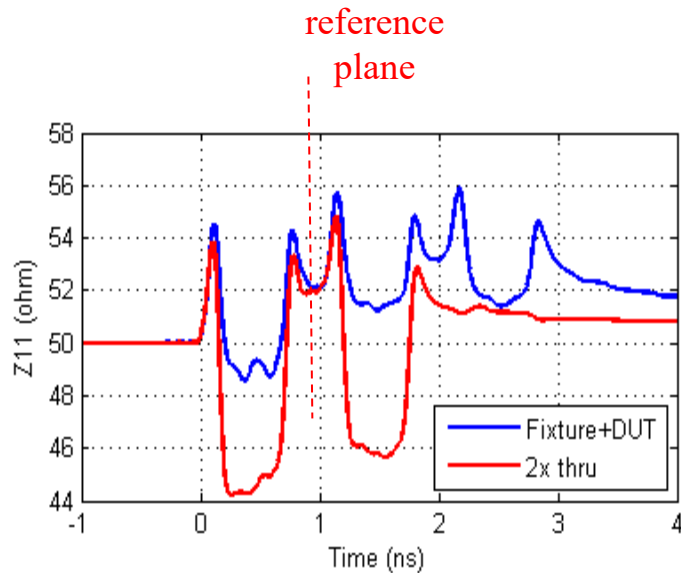
*模拟可能的PCB阻抗变化



不正确的RL不适合DK / DF / SR提取。

2x thru vs. 夹具阻抗

- ISD 去嵌入夹具阻抗, 不是 2x thru的阻抗.



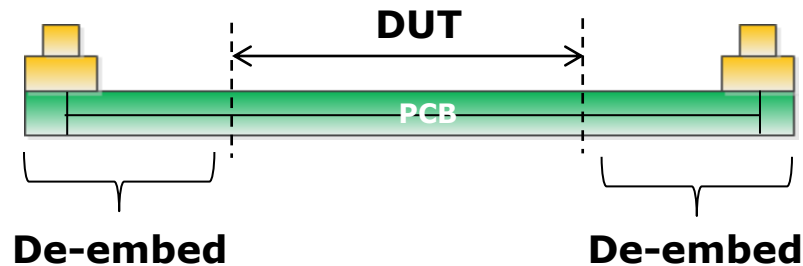
示例6: PCB 走线衰减

ISD vs. eigenvalue (Delta-L)

- 从长走线中去嵌入短走线得到走线的衰减。

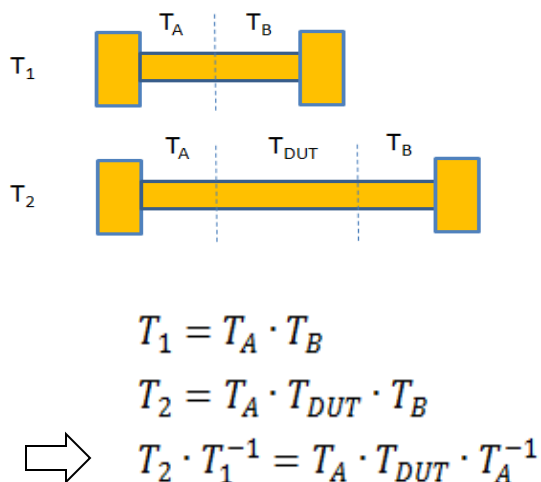


$$L_{\text{DUT}} = L_{\text{LONG}} - L_{\text{SHORT}}$$



特征值解决方案：不去嵌入仅用于计算走线衰减

- 将S转换为T以获取短和长的走线结构
- 假设短走线和长走线结构的左侧和右侧相同
- 假设DUT是统一的传输线
- 仅跟踪衰减被写在一个公式中



For uniform transmission line:

$$T_{DUT} = P \cdot \begin{pmatrix} e^{-\gamma l} & 0 \\ 0 & e^{+\gamma l} \end{pmatrix} \cdot P^{-1}$$

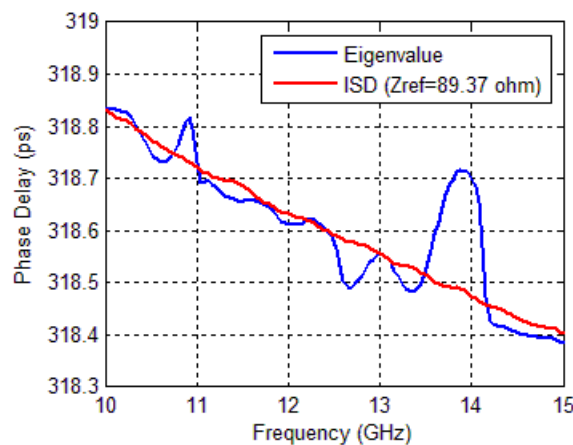
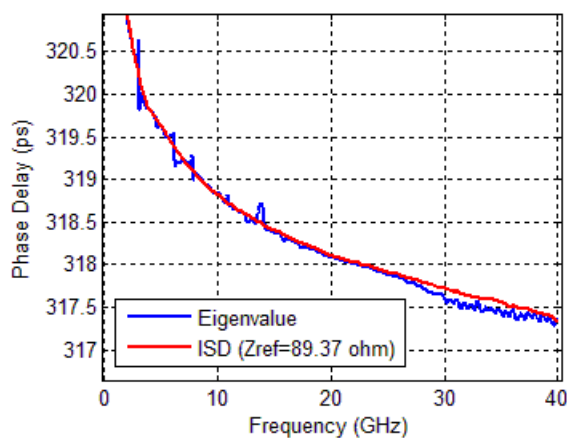
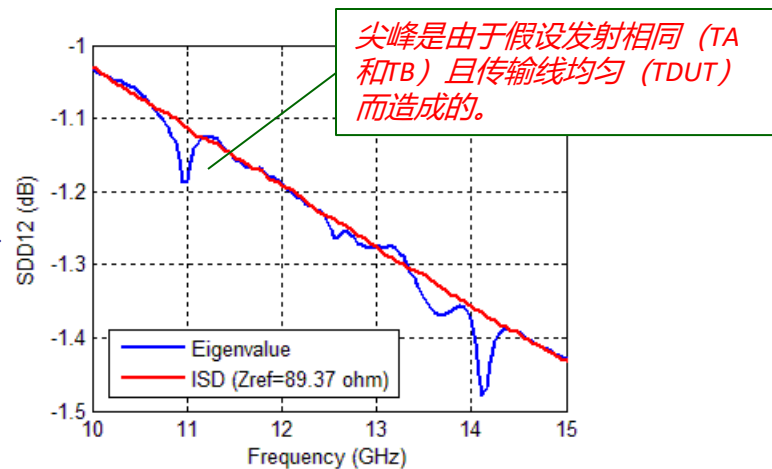
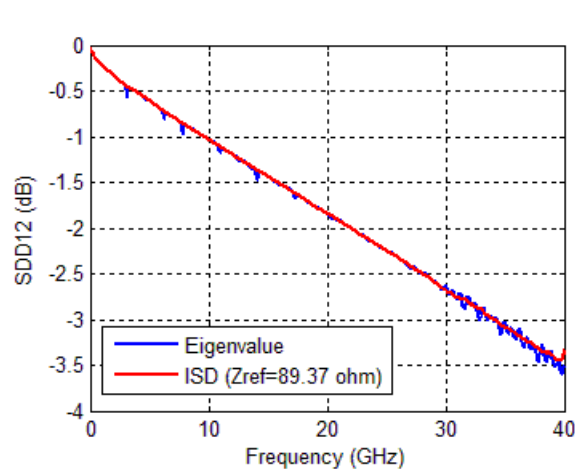
Let $T_2 \cdot T_1^{-1} = \begin{pmatrix} a & b \\ c & d \end{pmatrix}$

$\Rightarrow e^{-\gamma l} = \frac{(a+d) \pm \sqrt{(a-d)^2 + 4bc}}{2}$

eigenvalue

modal propagation constant

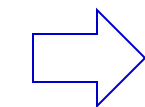
情况1: $2'' (= 7'' - 5'')$ 走线衰减特征值解决方案 容易出现尖峰



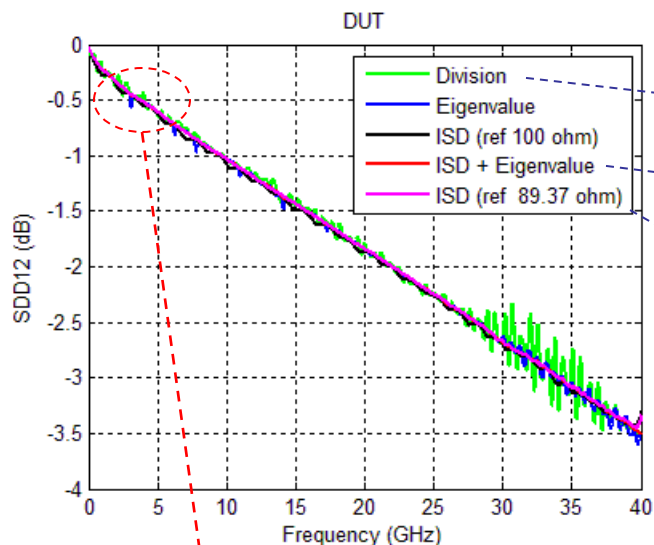
ISD的无尖峰结果有助于以后提取DK和DF

一键即可将ISD与特征值进行比较，还有更多...

Run	Help
Split 2x Thru only	
Extract DUT	
Batch mode	
Eigenvalue (Delta-L) method	
Compare ISD with Eigenvalue	
Renormalize and deskew DUT	
Material Property Extraction (MPX)	



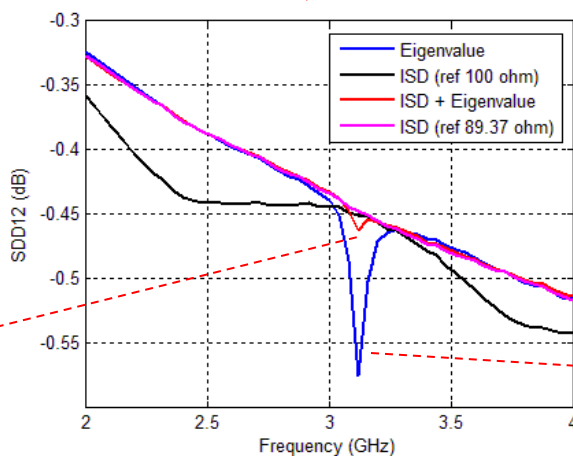
One click does it all



直接dB减法

ISD结果的特征值

重新标准化ISD结果
通过走线阻抗
(自动计算)



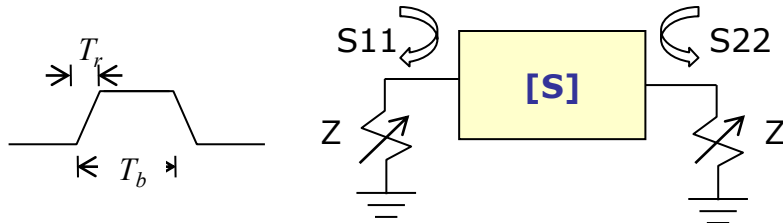
尖峰是由于相同发射 (TA和TB)
和统一传输线 (TDUT)

尖峰是由于假设TA和TB相同和
统一传输线 (TDUT)

如何定义走线阻抗

PCB走线是不均匀的传输线

- 通过最小的RL定义阻抗*

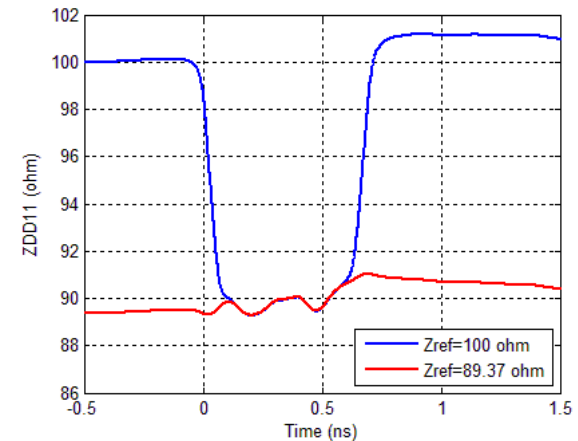
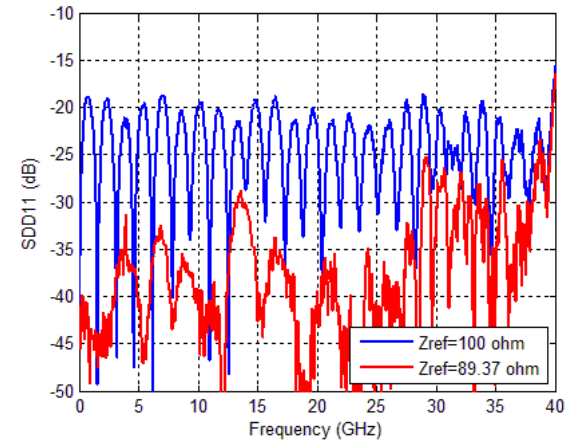
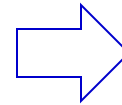


Minimize:

$$\varphi = \int_{f_{\min}}^{f_{\max}} \left\{ |S_{11}(f)|^2 + |S_{22}(f)|^2 \right\} \cdot |w(f)|^2 df$$

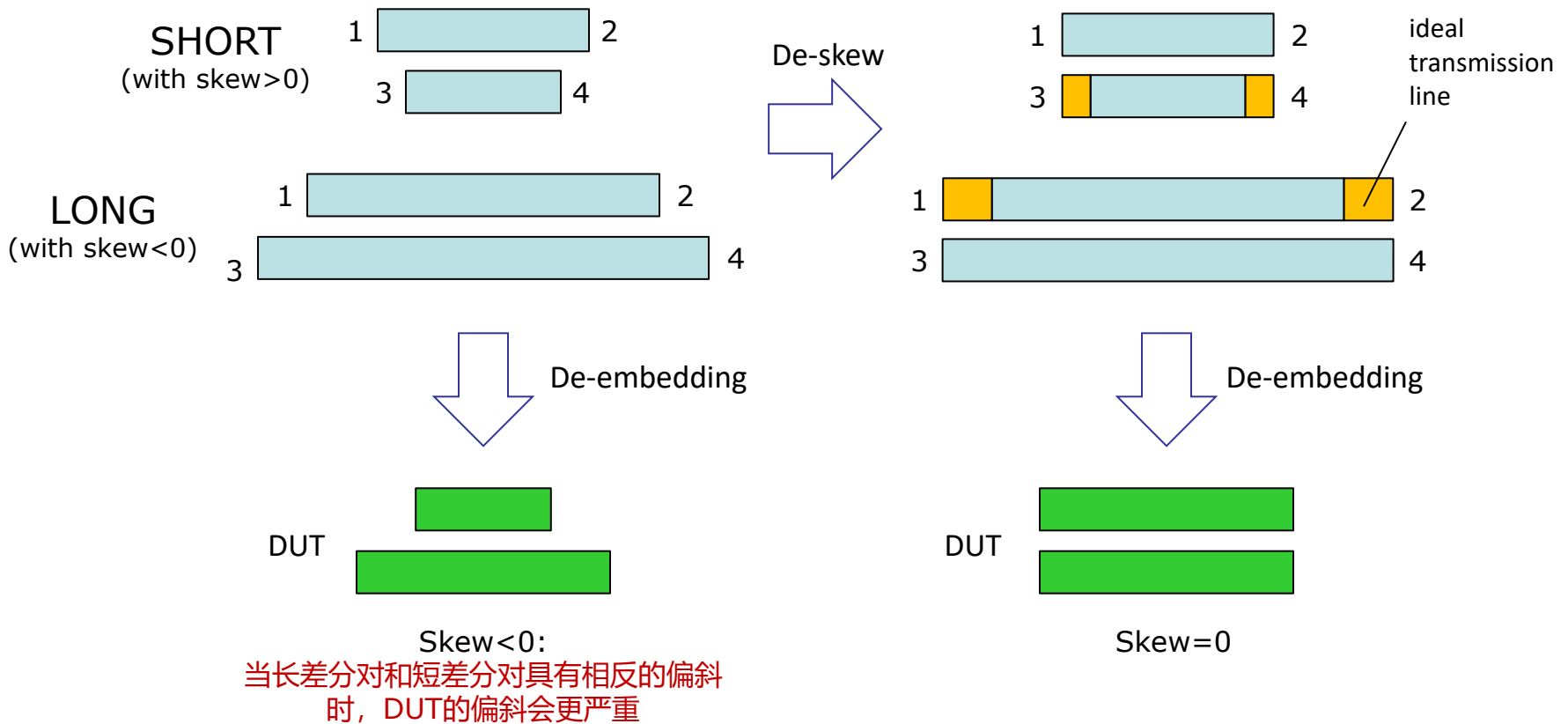
$$w(f) = \frac{\sin(\pi f T_r)}{\pi f T_r} \cdot \frac{\sin(\pi f T_b)}{\pi f T_b}$$

* J. Balachandran, K. Cai, Y. Sun, R. Shi, G. Zhang, C.C. Huang and B. Sen, "Aristotle: A fully automated SI platform for PCB material characterization," DesignCon 2017, 01/31-02/02/2017, Santa Clara, CA.

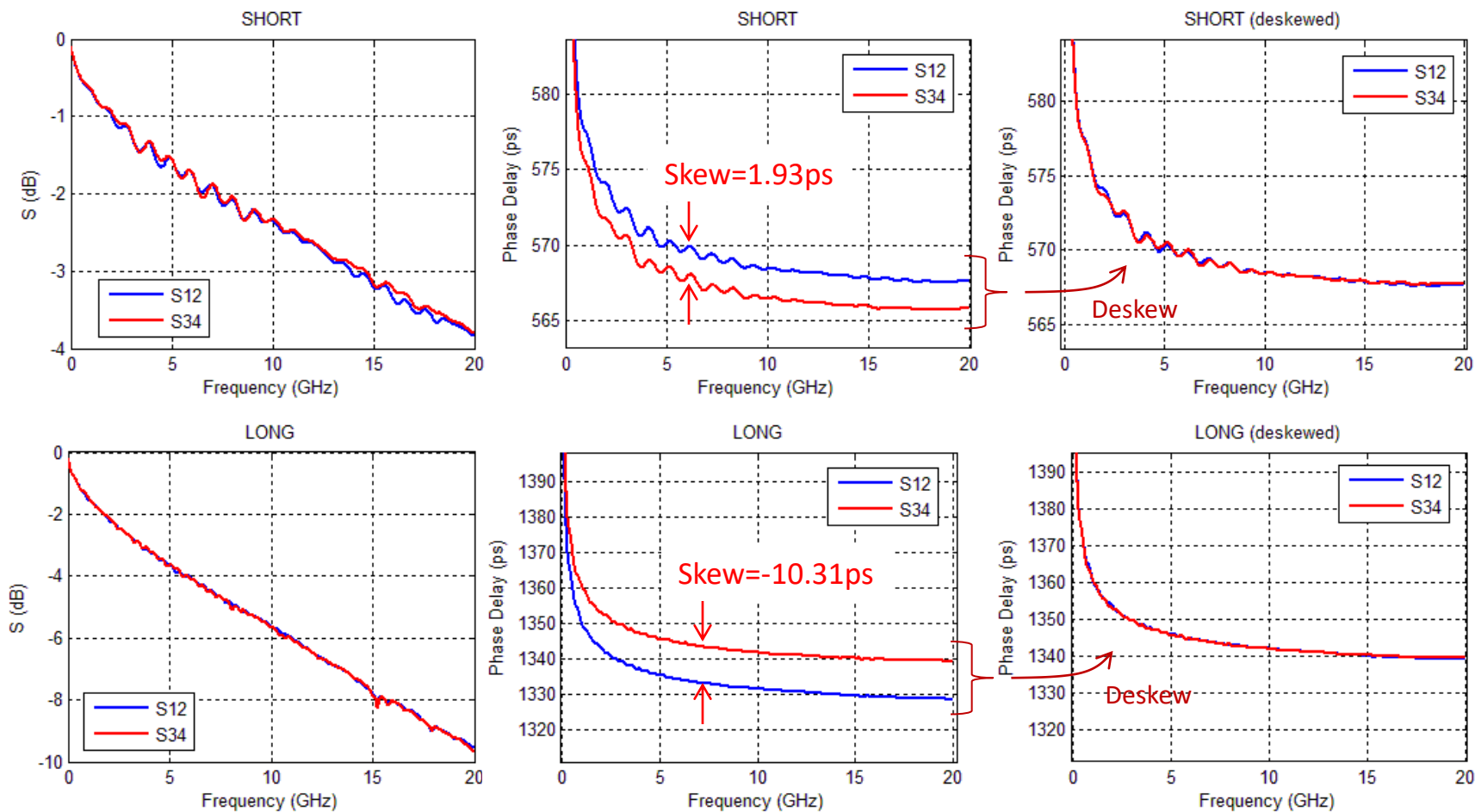


时间偏斜去嵌入

理想的传输线到偏斜去嵌入

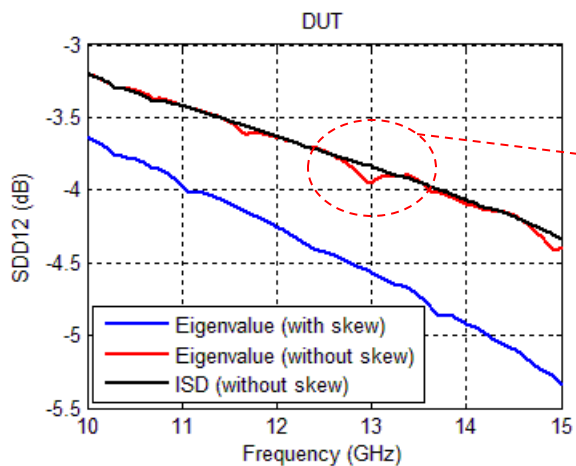
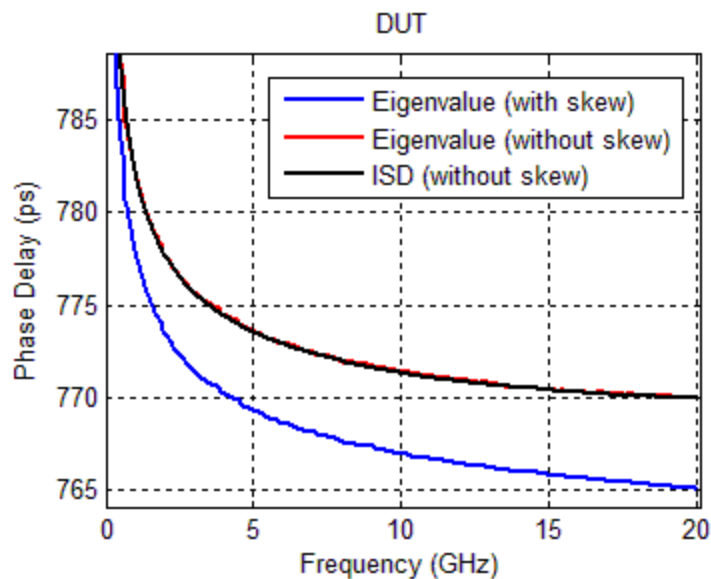
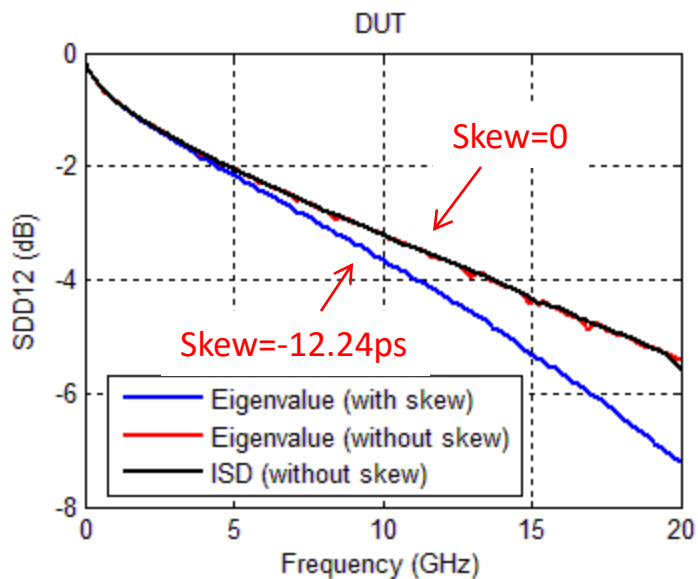


ISD可选地自动对原始数据进行时间偏移校正



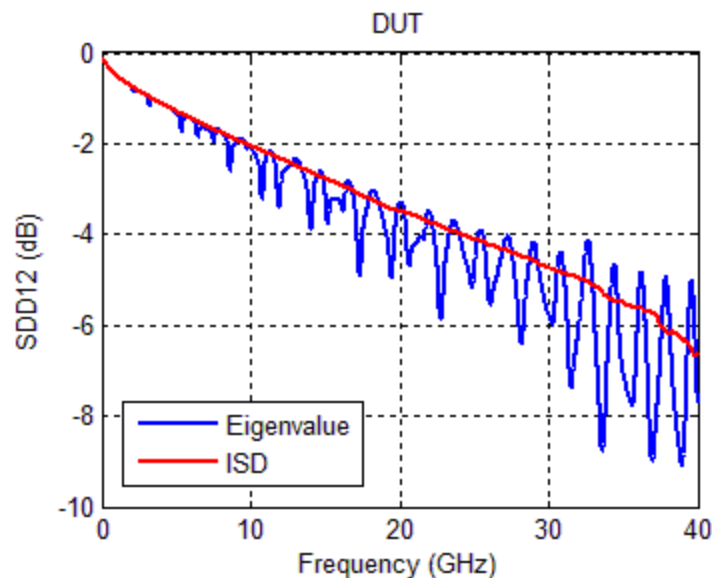
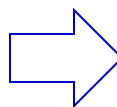
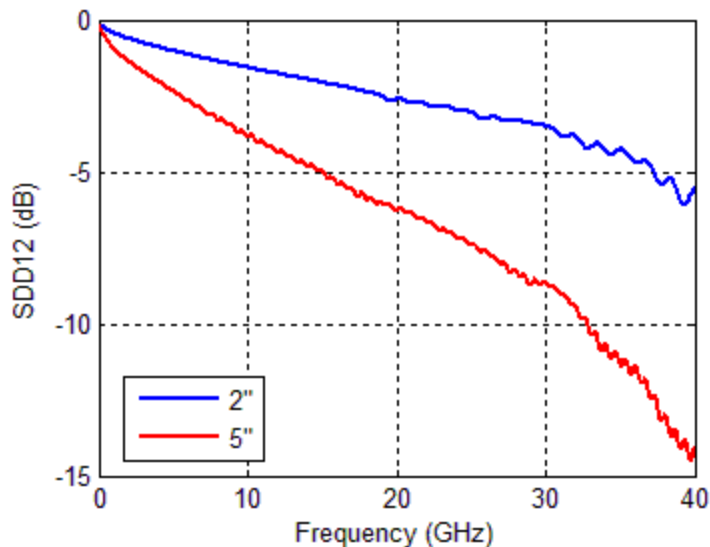
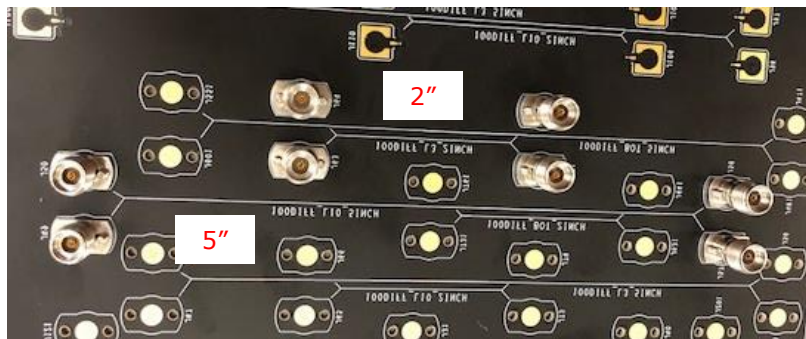
LONG=8"
SHORT=3"

情况2：无论有无时间差，提取的走线衰减都可能非常不同



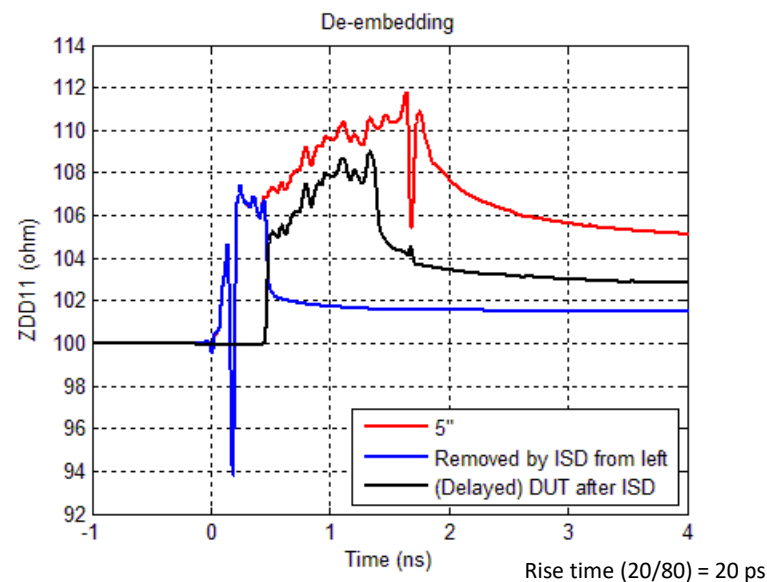
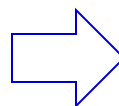
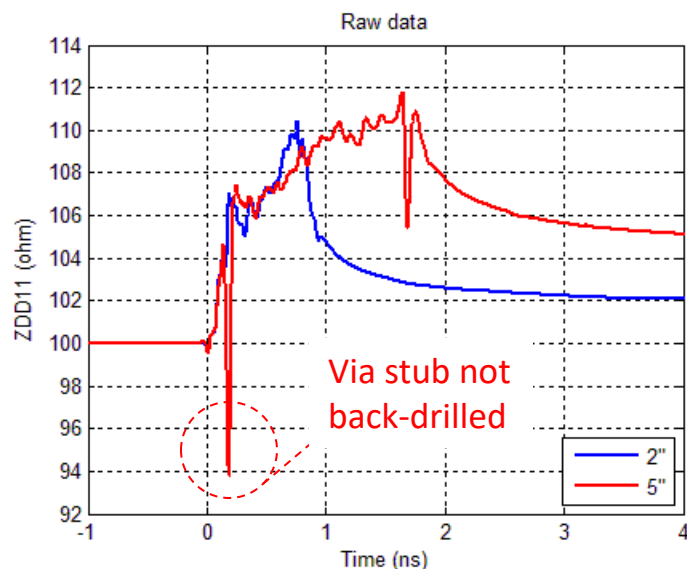
特征值解决方案在一个有趣的频率 (大约12.9 GHz) 上有一个下降

情况3：在这种情况下，特征值 (Delta-L) 解变得不稳定，但是为什么呢？



TDR of raw data reveals why... 2" structure was back-drilled but 5" was not

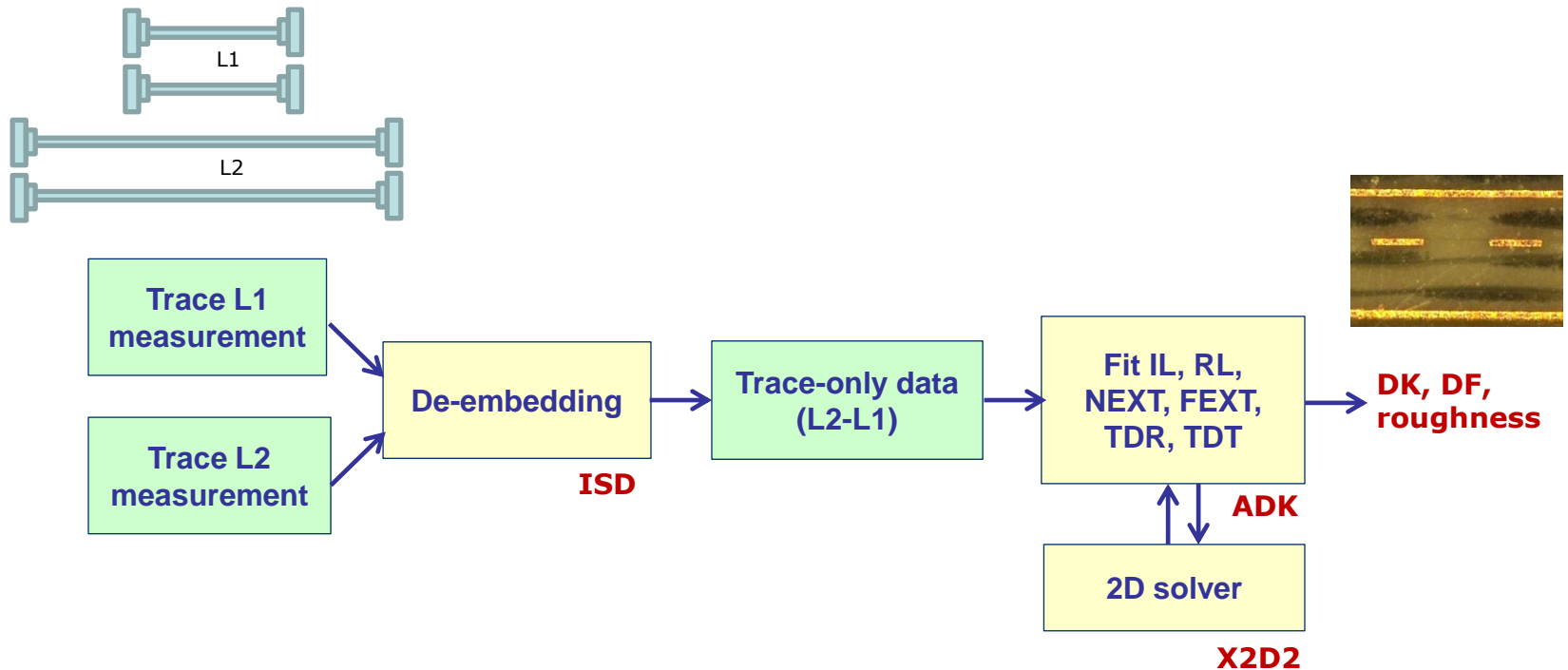
- Eigenvalue solution assumes 2" and 5" structures have identical launches.
- ISD de-embeds 5" structure's launch correctly.



ISD saves \$\$\$ and time for not spinning another board.

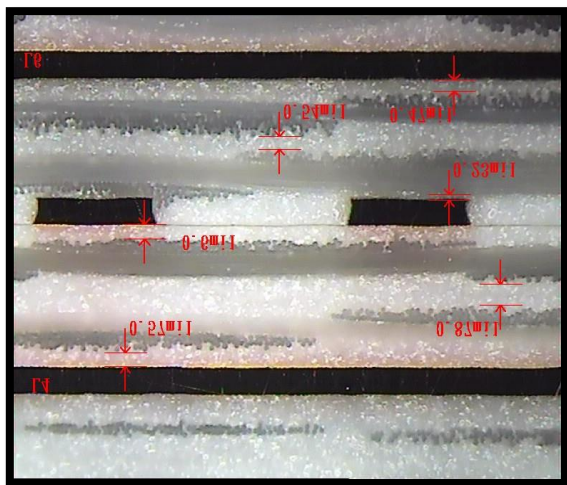
示例7：材料属性提取DK, DF和粗糙度

- 仅通过匹配去嵌入的走线数据的所有IL, RL, NEXT, FEXT和TDR / TDT的自一致方法来提取DK, DF和粗糙度

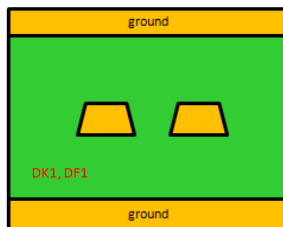


Automated extraction flow

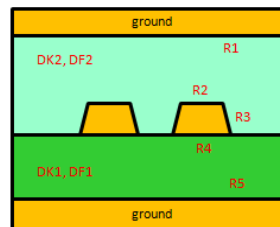
横截面模型



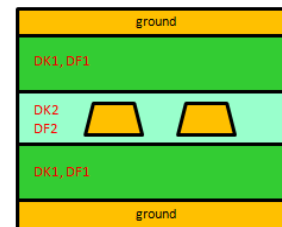
优化变量：
 DK1, DF1, DK2, DF2
 R1, R2, R3, R4, R5 (粗糙度)
 金属宽度和间距



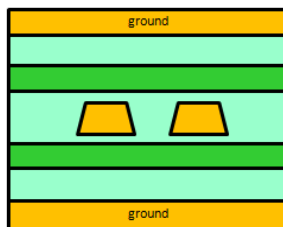
Model 1



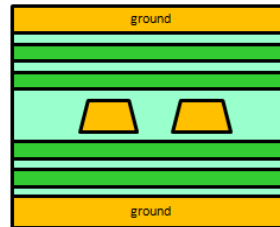
Model 2



Model 3



Model 4



Model 5

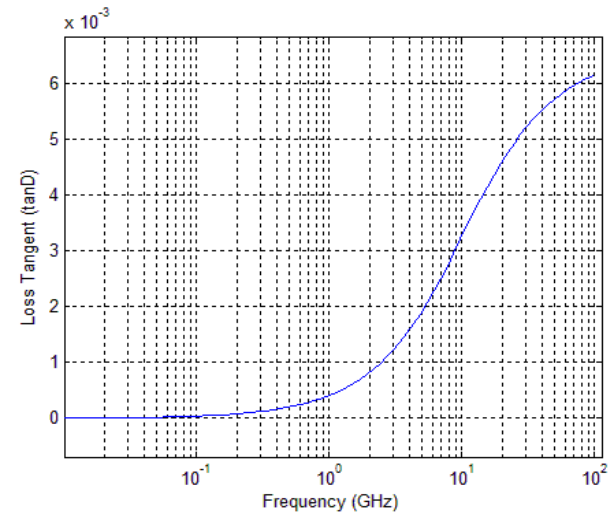
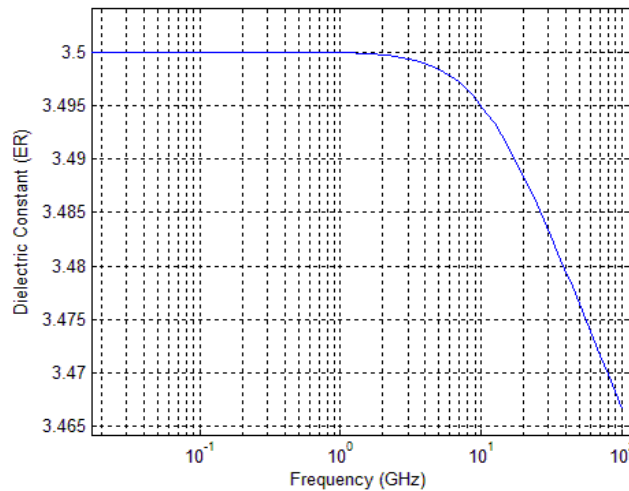
因果介电模型

- 宽带德拜（或Djordjevic-Sarkar）模型

- 只需要4个变量：

$$\varepsilon_{\infty} , \Delta\varepsilon , m_1 , m_2$$

$$\varepsilon = \varepsilon_{\infty} + \Delta\varepsilon \cdot \frac{1}{m_2 - m_1} \cdot \log_{10} \left(\frac{10^{m_2} + i \cdot f}{10^{m_1} + i \cdot f} \right)$$
$$= \varepsilon_r \cdot (1 - i \cdot \tan \delta)$$



$$\varepsilon_{\infty} = 3.35 , \Delta\varepsilon = 0.15 , m_1 = 10 , m_2 = 14.5$$

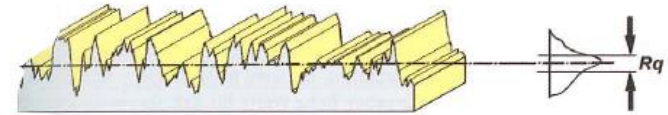
表面粗糙度模型

- 有效电导率 (由G. Gold和K. Helmreich在DesignCon 2014上发表) 仅需两个变量: σ_{bulk} , R_q

Parameter	Description	Standard
R_q	root mean square	DIN EN ISO 4287
R_a	arithmetic average	DIN EN ISO 4287, ANSI B 46.1
R_t	core roughness depth	DIN EN ISO 13565
R_z	average surface roughness	DIN EN ISO 4287

Table 1: Statistical parameters to describe surface roughness

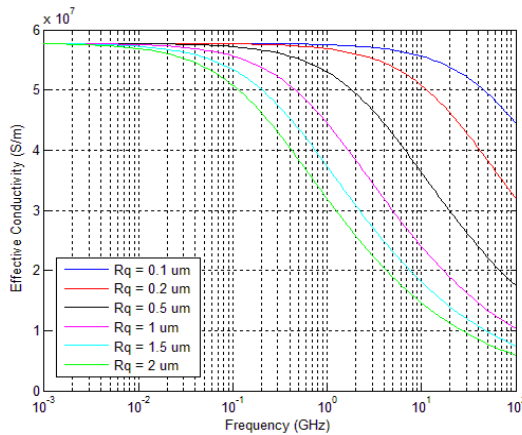
$$\sigma(x) = \sigma_{bulk} \cdot CDF(x) = \sigma_{bulk} \cdot \int_{-\infty}^x PDF(x) du = \sigma_{bulk} \cdot \int_{-\infty}^x e^{-\frac{u^2}{2R_q^2}} du$$



- 在数值上求解功率

$$\nabla^2 \bar{B} - j\omega\mu\sigma\bar{B} + \frac{\nabla\sigma}{\sigma} \times (\nabla \times \bar{B}) = 0 \text{ 和使功率等于光滑表面的}$$

$$\sigma_{eff}$$



$$\sigma_{bulk} = 5.8 \times 10^7 \text{ s/m}$$

- ❖ 简单
- ❖ 与场求解器一起很好地工作 给出粗糙度对所有IL, RL, NEXT和FEXT的影响

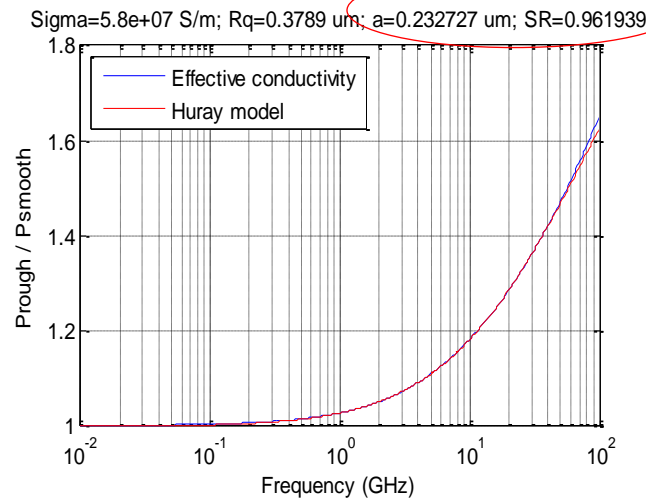
将有效电导率转换为Huray模型

- Huray model

$$\frac{P_{rough}}{P_{smooth}} \approx 1 + \frac{3}{2} \cdot SR \cdot \left(\frac{1}{1 + \frac{\delta(f)}{a} + \frac{1}{2} \left(\frac{\delta(f)}{a} \right)^2} \right)$$

$$\delta(f) = \sqrt{\frac{1}{\pi f \mu \sigma}} ; a = \text{radius} ; SR = \text{surface ratio}$$

- Curvefit* P_{rough} / P_{smooth} to convert σ_{bulk} , R_q to a , SR



*Automated in ADK

DK/DF/SR 提取 (from ADK)

Extract DK, DF and Roughness

Tools

Extract DK, DF and Roughness

Touchstone File (Trace only)

Browse ... D:\MPX_L7_T5_WS1_Z90_T1234.s4p_DUT.s4p

Trace only
 Delta L

Stripline (Three layers)

Length = 2 inch
From 0 to 100 GHz

Cross section (in mil)

td1	4.65	td2	1.19
td3	2.38	td4	3.85
tm	1.21	pitch	14.971
wt	5.504	wb	5.799

Fixed
 Thickness Width All

DK & DF at 1 GHz

DK	3.439	DF	0.004123
DK2	3.628	DF2	0.000664

Fixed M1=7.840 M2=16.98

Roughness (Rq)

Top ground	0.3103	um
Signal	0.3103 0.3	um
Bottom ground	0.3103	um
Sigma	5.8e7	S/m

Fixed Rq

Auto de-skew

Run

Create new Touchstone file

Length	2	inch
Minimum Frequency	0	GHz
Maximum Frequency	40	GHz
Number of Points	801	

Linear Log

Reference Impedance 50 Ohm

Simulate Only

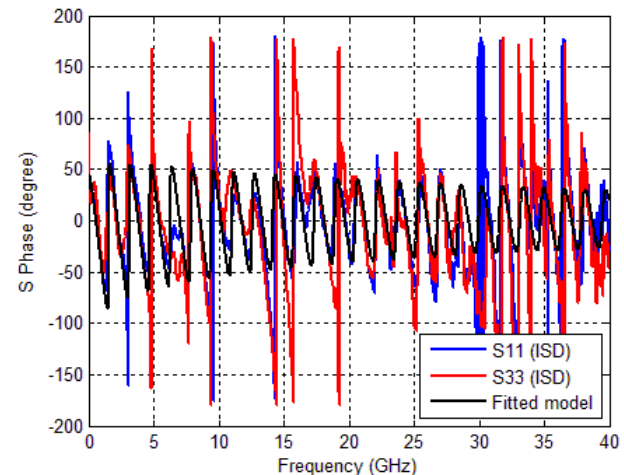
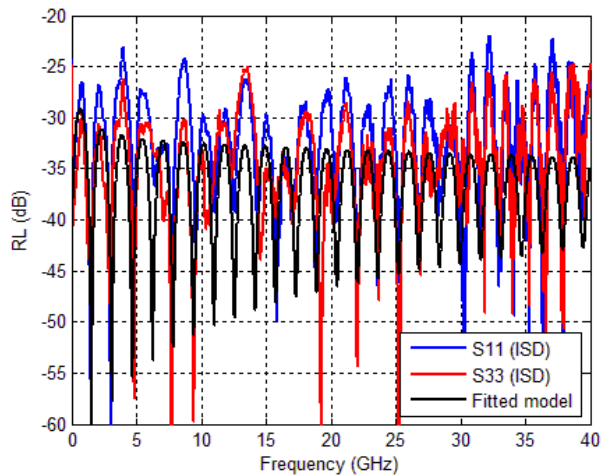
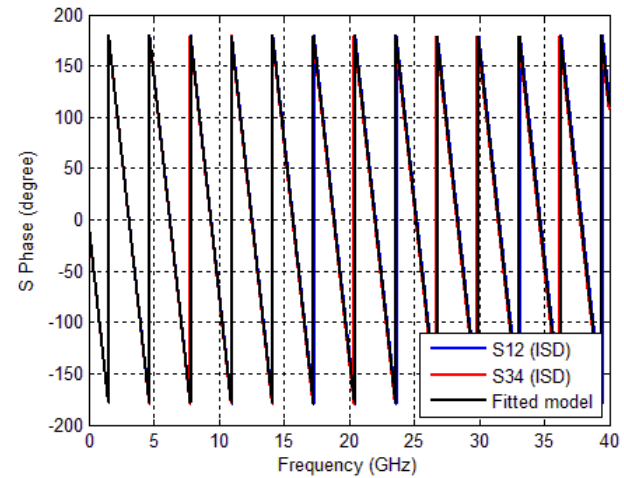
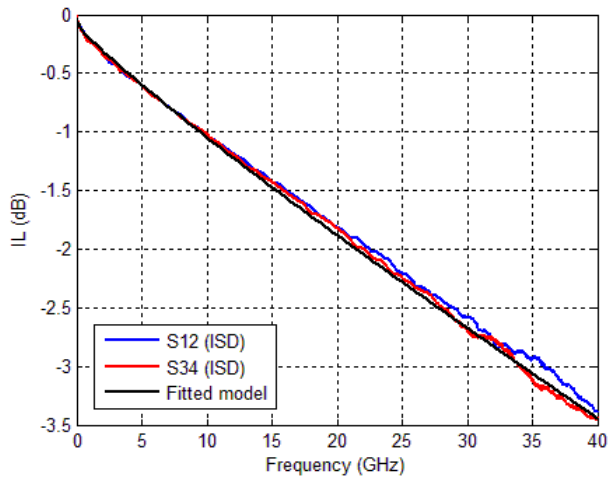
* Optimized

Multiple templates

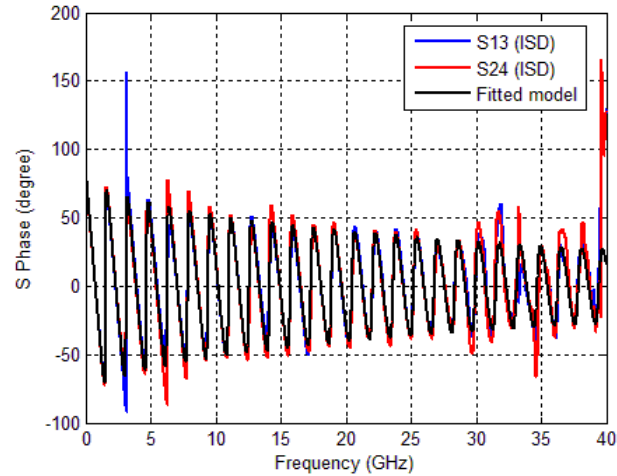
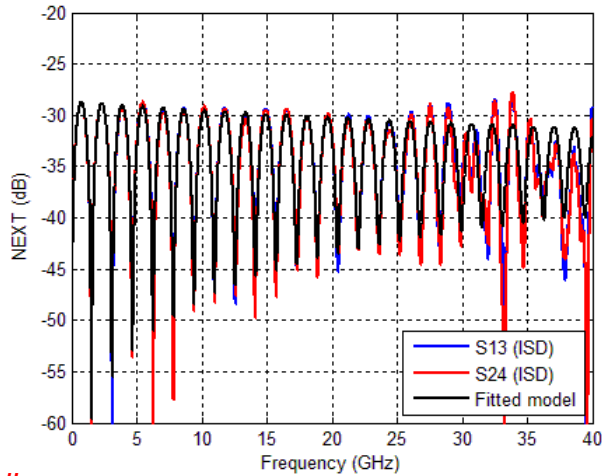
Updated after extraction

Different roughness for each surface

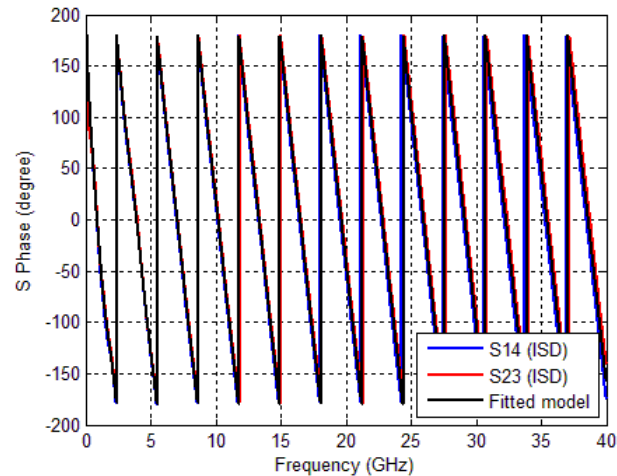
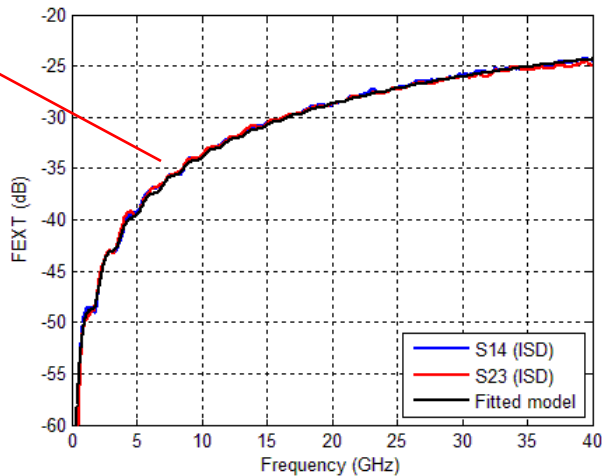
IL and RL 匹配



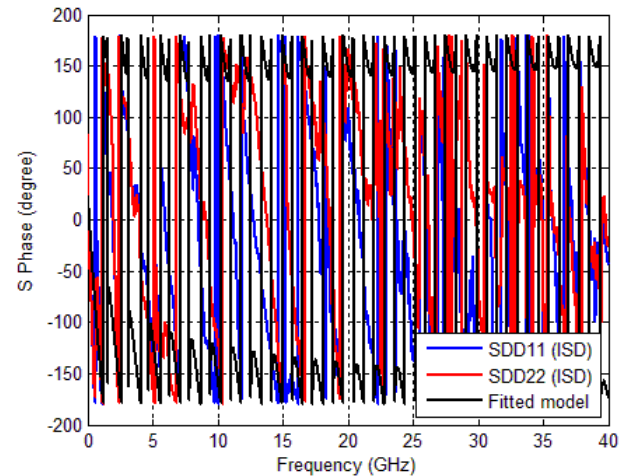
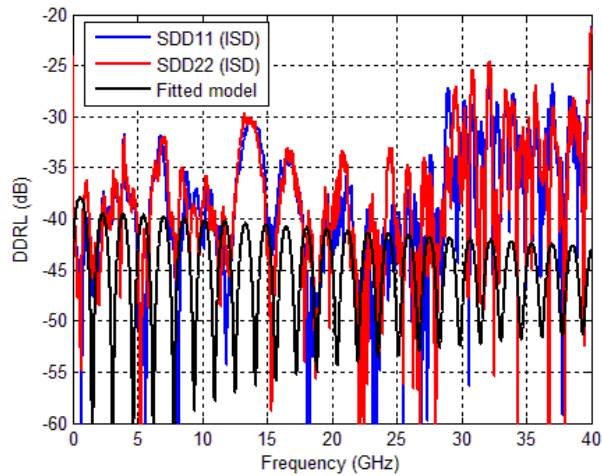
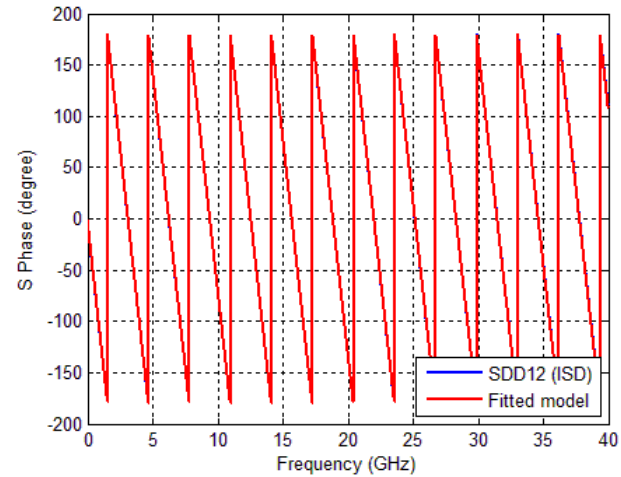
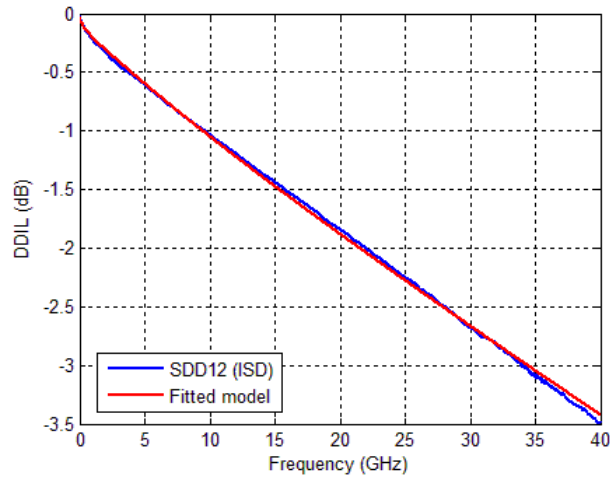
NEXT and FEXT 匹配



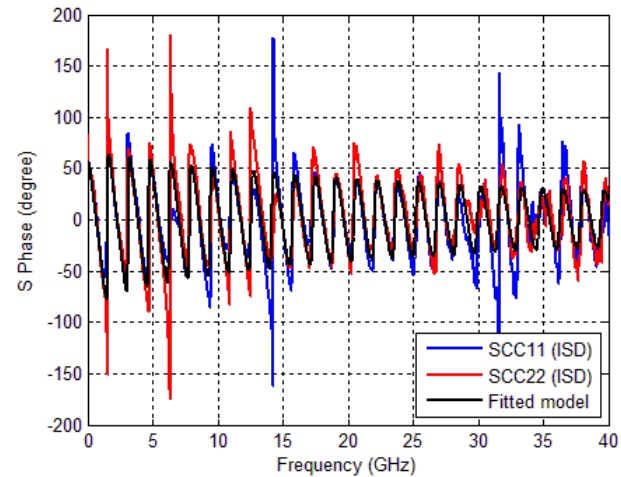
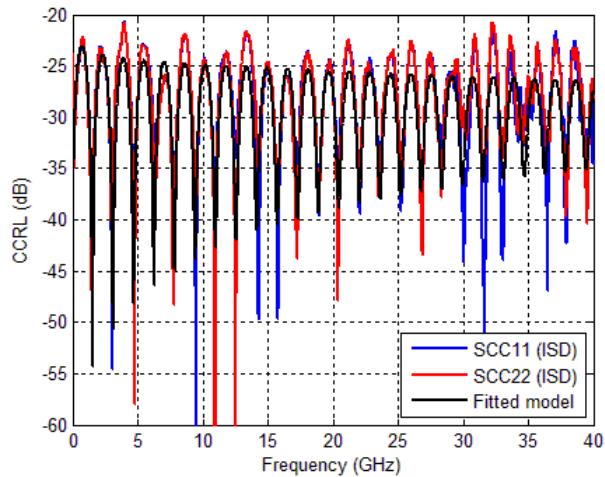
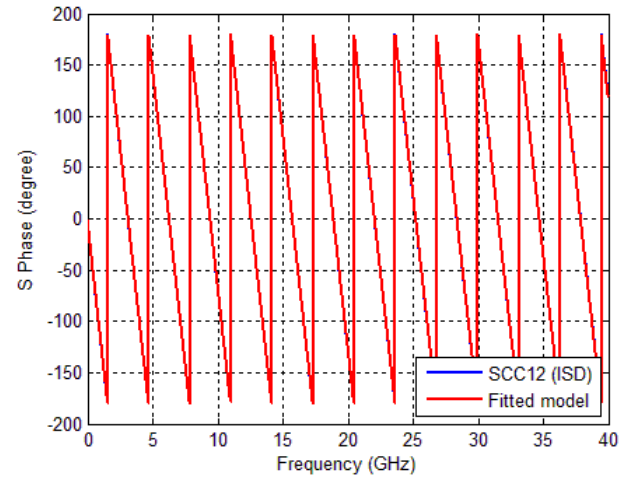
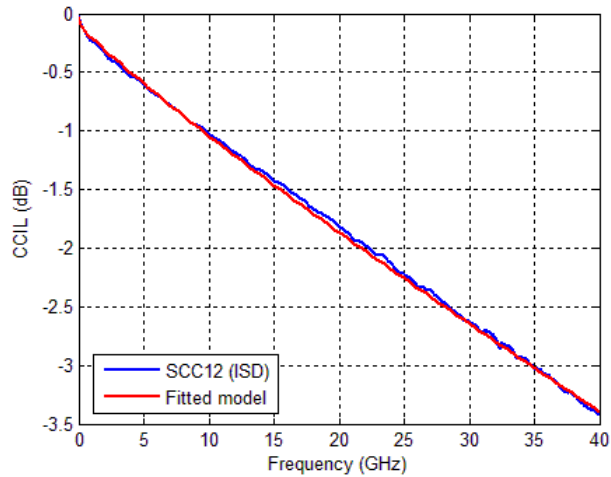
Large FEXT implies inhomogeneous dielectric



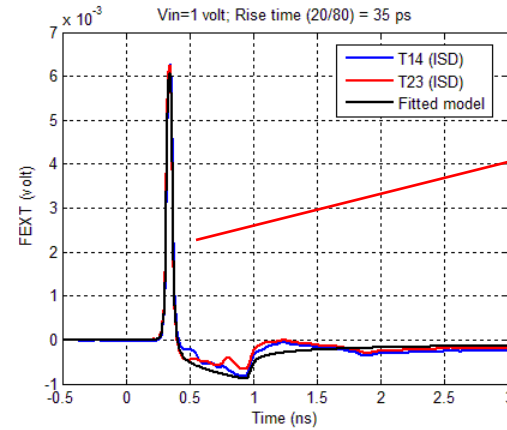
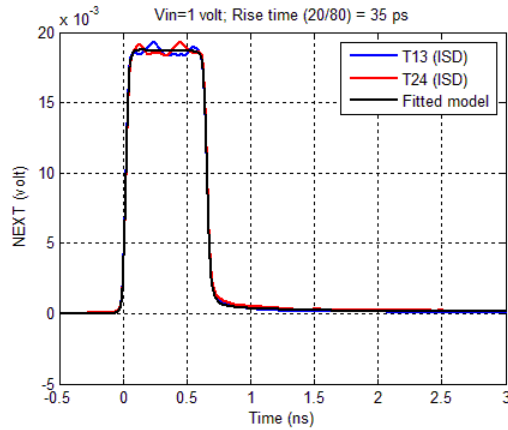
DDIL and DDRL 匹配



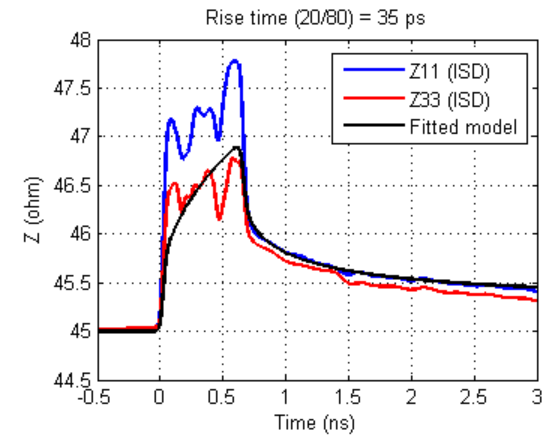
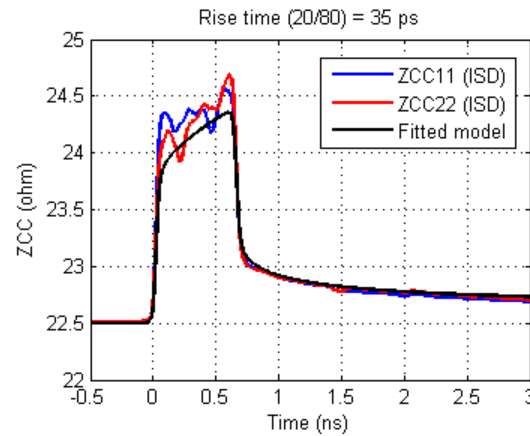
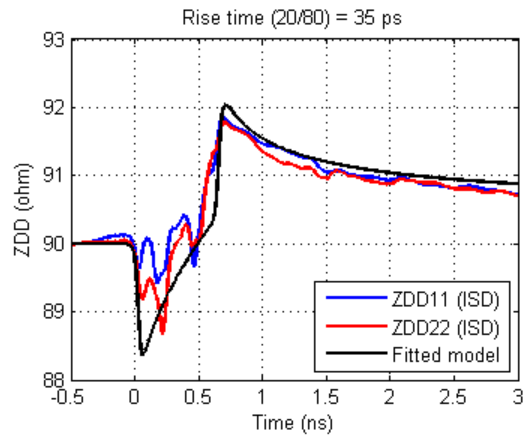
CCIL and CCRL 匹配



TDT and TDR匹配

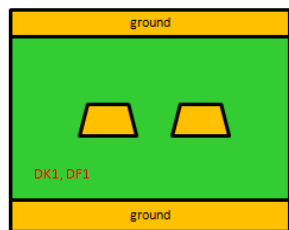


Positive polarity implies $K_C > K_L$

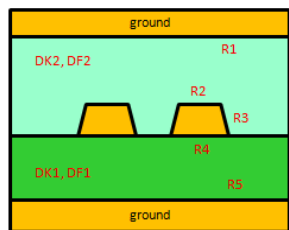


5种模型的比较

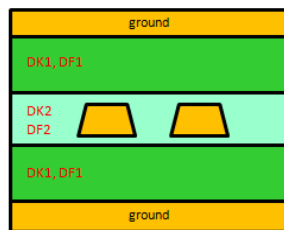
- 模型1无法匹配FEXT。模型2至5可以很好地匹配所有IL, RL, NEXT, FEXT和TDR / TDT



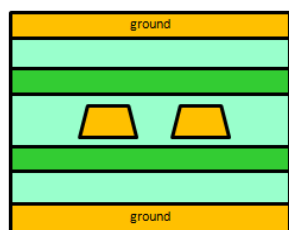
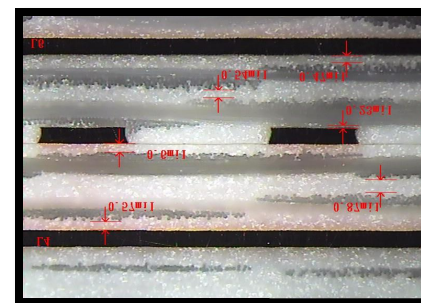
Model 1



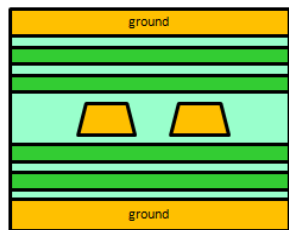
Model 2



Model 3



Model 4



Model 5

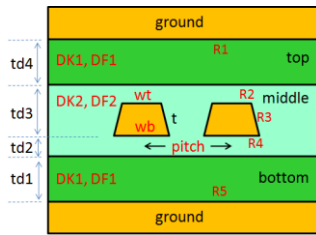


Model	DK1	DK2
1	3.510	-
2	2.444	4.294
3	3.413	3.623
4	3.863	3.360
5	3.115	3.975

At 10 GHz

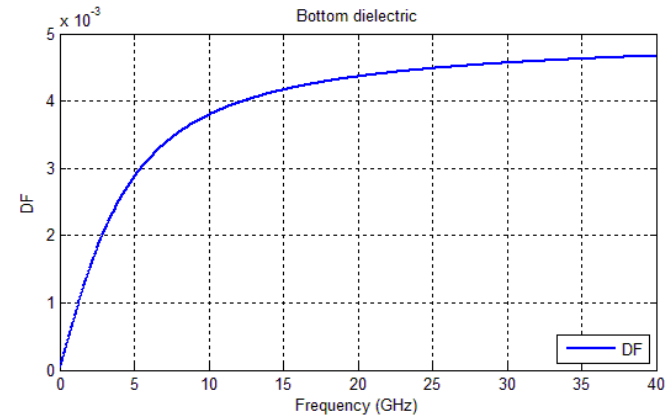
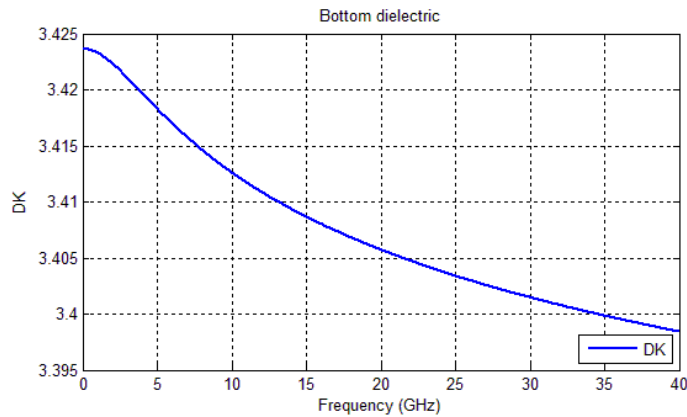
DK2 > DK1 because of positive-polarity FEXT

提取 DK1 和 DF1 模型3

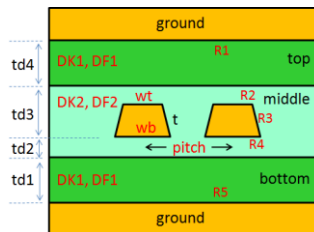


$$\begin{aligned}\varepsilon_{\infty} &= 3.27929 \\ \Delta\varepsilon &= 0.144348 \\ m1 &= 9.58619 \\ m2 &= 15.4109\end{aligned}$$

$$\begin{aligned}\varepsilon &= \varepsilon_{\infty} + \Delta\varepsilon \cdot \frac{1}{m_2 - m_1} \cdot \log_{10} \left(\frac{10^{m_2} + i \cdot f}{10^{m_1} + i \cdot f} \right) \\ &= \varepsilon_r \cdot (1 - i \cdot \tan \delta)\end{aligned}$$

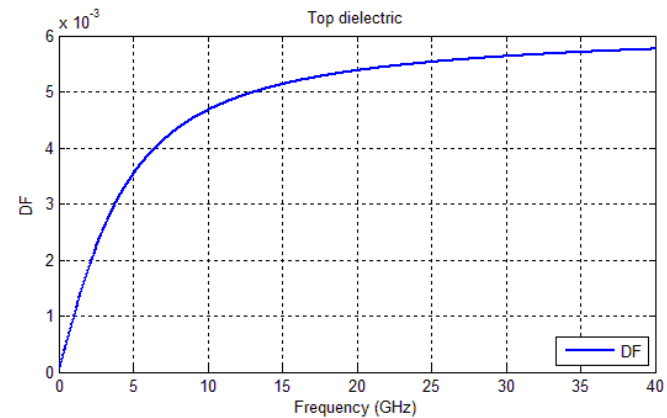
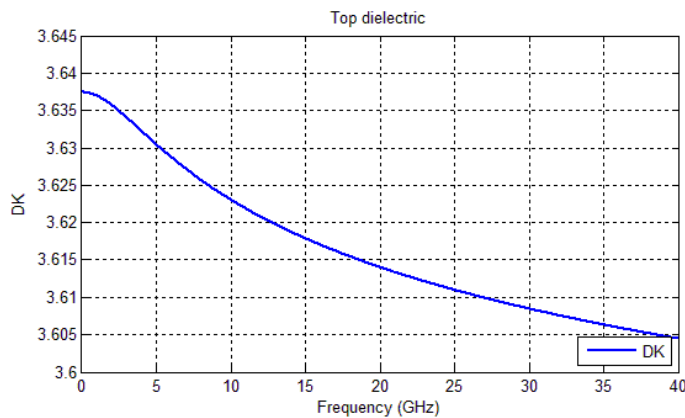


提取 DK2 和 DF2 模型3

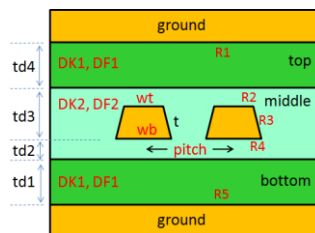


$$\begin{aligned}\varepsilon_{\infty} &= 3.46724 \\ \Delta\varepsilon &= 0.170196 \\ m1 &= 9.58715 \\ m2 &= 14.8352\end{aligned}$$

$$\begin{aligned}\varepsilon &= \varepsilon_{\infty} + \Delta\varepsilon \cdot \frac{1}{m_2 - m_1} \cdot \log_{10} \left(\frac{10^{m_2} + i \cdot f}{10^{m_1} + i \cdot f} \right) \\ &= \varepsilon_r \cdot (1 - i \cdot \tan \delta)\end{aligned}$$

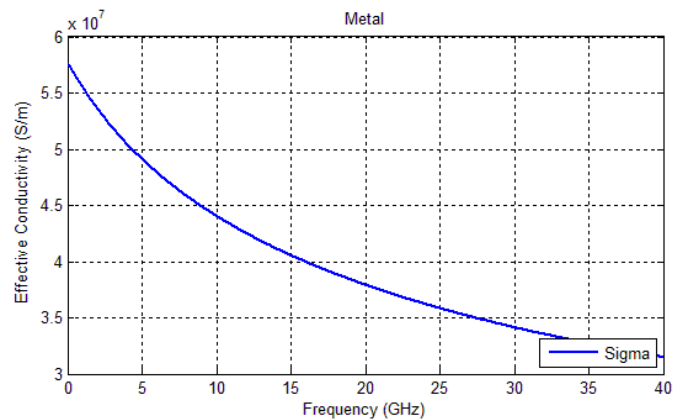


提取有效电导率 模型 3

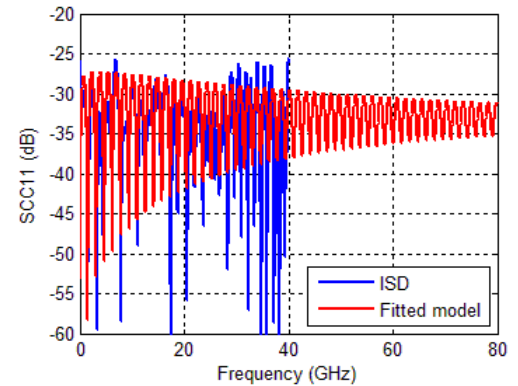
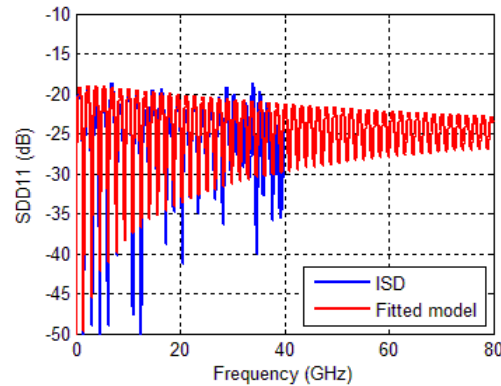
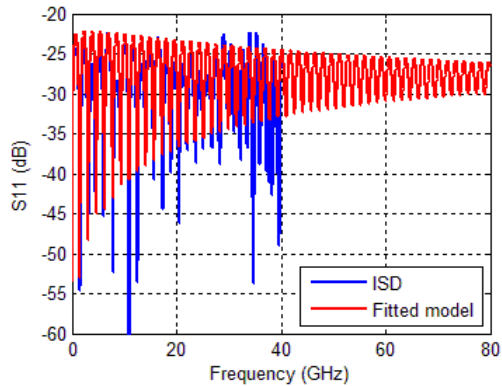
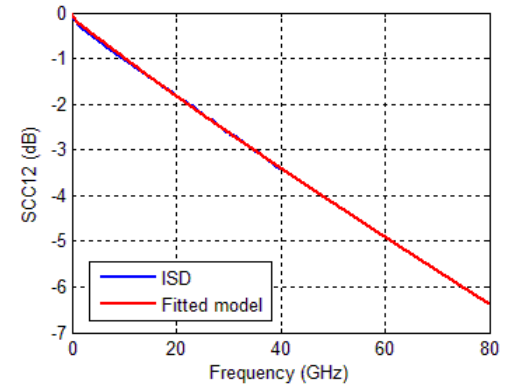
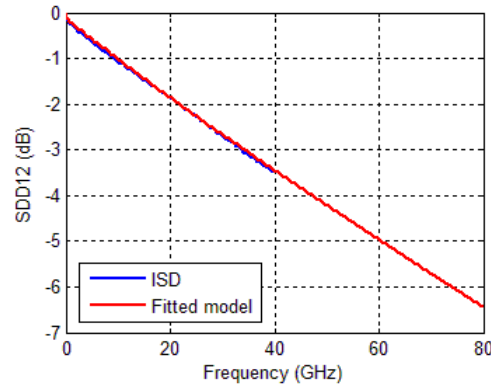
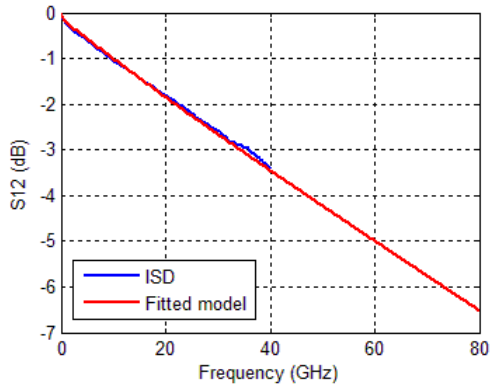


$$\sigma = 5.8 \times 10^7 \text{ S/m}$$

$$R_q = 0.324321 \mu\text{m}$$



可以创建长度和频率可缩放的模型.



Summary

- 准确的去嵌入对于设计验证，一致性测试和PCB材料属性（DK, DF, 粗糙度）提取至关重要。
- 如果测试夹具和校准结构具有不同的阻抗，则传统的去嵌入方法会在被测设备（DUT）结果中产生非因果错误。
- 原位去嵌入（ISD）通过软件而非硬件解决了此类阻抗差异，从而提高了去嵌入精度，同时降低了硬件成本。

Reference

- C.C. Huang, "Fixture de-embedding using calibration structures with open and short terminations," US patent no. 9,797,977, 10/24/2017.
- C.C. Huang, "In-Situ De-embedding," EDI CON, Beijing, China, 04/19 to 04/21/2016.
- C. Luk, J. Buan, T. Ohshida, P.J. Wang, Y. Oryu, C.C. Huang and N. Jarvis, "Hacking skew measurement," DesignCon 2018, 01/30 to 02/01/2018, Santa Clara, CA.
- H. Barnes, E. Bogatin, J. Moreria, J. Ellison, J. Nadolny, C.C. Huang, M. Tsiklauri, S.J. Moon, V. Herrmann, "A NIST traceable PCB kit for evaluating the accuracy of de-embedding algorithms and corresponding metrics," DesignCon 2018, 01/30 to 02/01/2018, Santa Clara, CA.
- J. Moreira, C.C. Huang and D. Lee, "DUT ATE test fixture S-parameters estimation using 1x-reflect methodology," BiTS China Workshop, 09/07/2017, Shanghai, China.
- J. Balachandran, K. Cai, Y. Sun, R. Shi, G. Zhang, C.C. Huang and B. Sen, "Aristotle: A fully automated SI platform for PCB material characterization," DesignCon 2017, 01/31-02/02/2017, Santa Clara, CA.